

IRIS detector studies in vacuum: status and plans

Giuseppe BRUNO, Pasquale CARIOLA, Domenico COLELLA,
Cosimo PASTORE, Triloki TRILOKI, Antonio VALENTINI, and Vincenzo VALENTINO

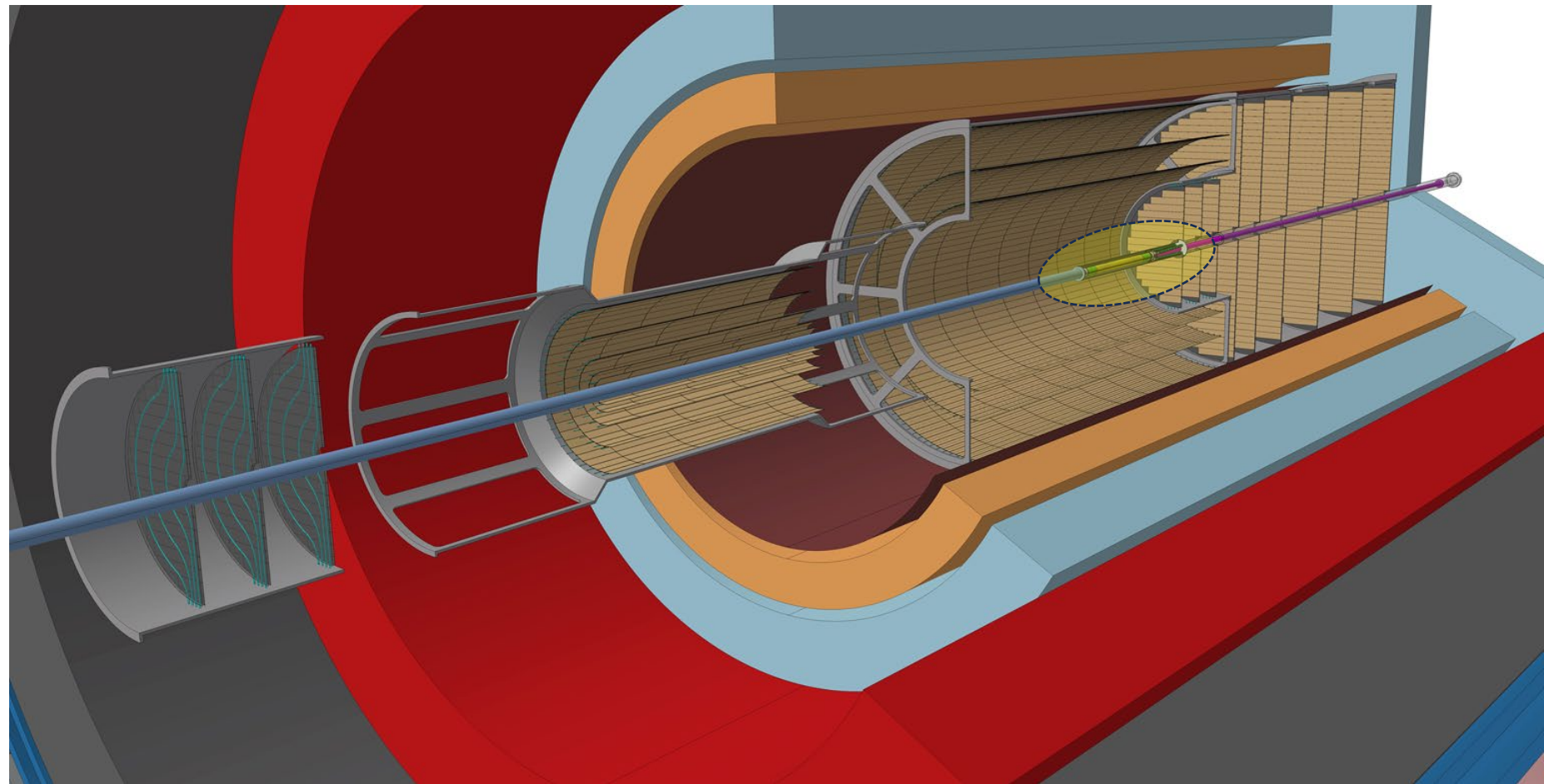
INFN Bari, Bari-Italy



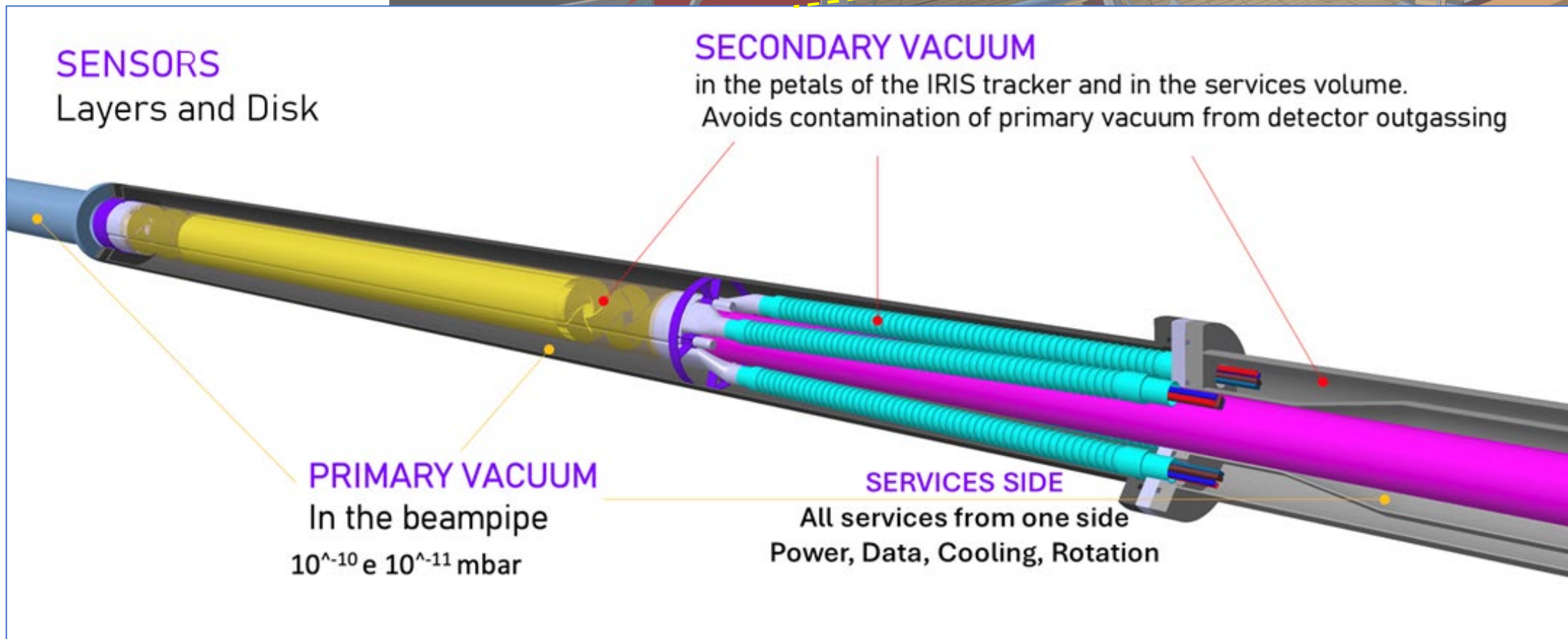
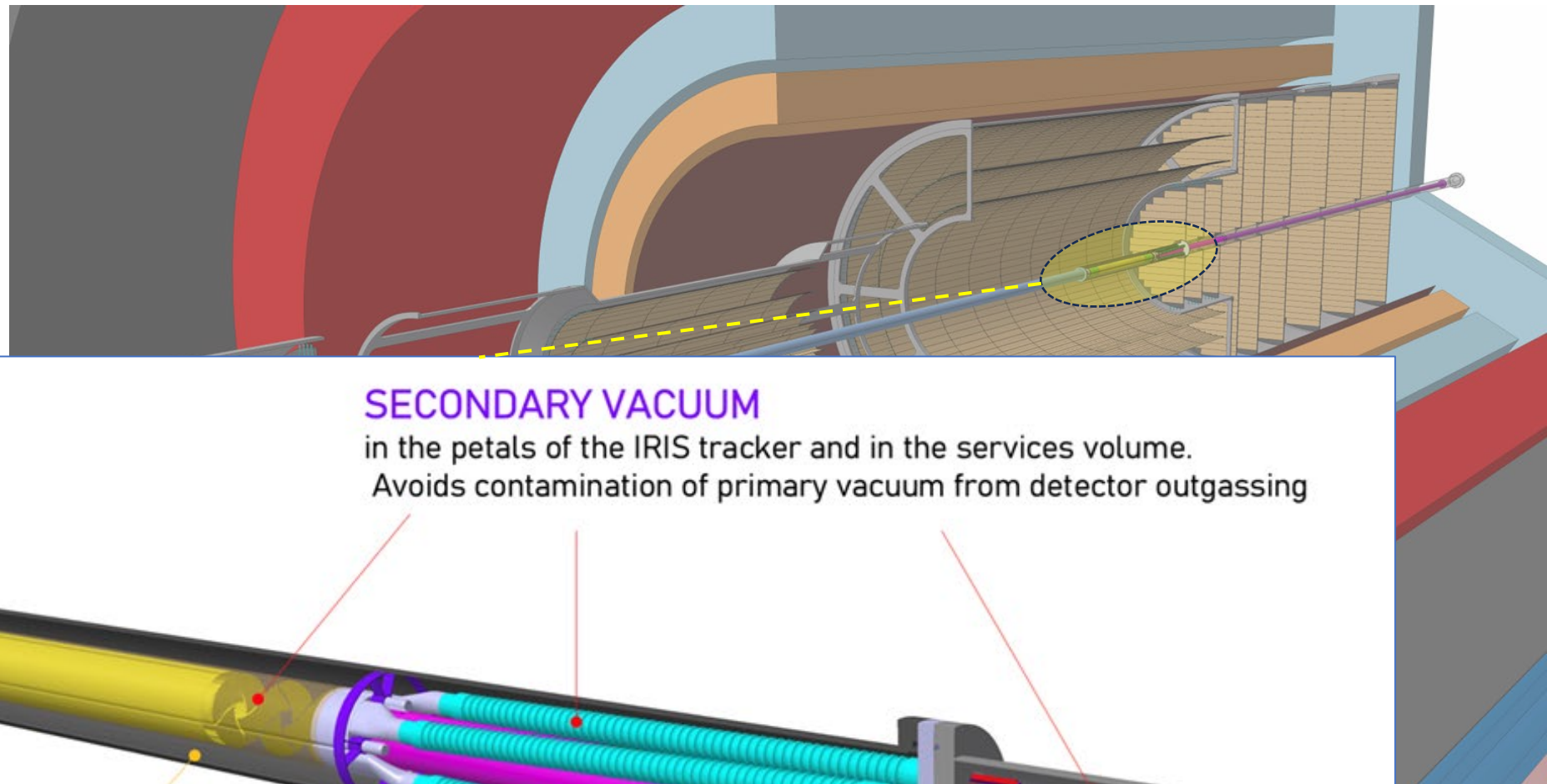
Contents

- Motivation
- Preliminary results
 - Present experimental setup
 - Outgassing study
 - Residual gas atmosphere study
 - Total mass loss (TML) study
 - Wire bonding strength study
- Available experimental facilities
- Future plans

IRIS detector @ ALICE3



IRIS detector @ ALICE3



How to perform outgassing measurement?

There are three ways to perform outgassing measurement:

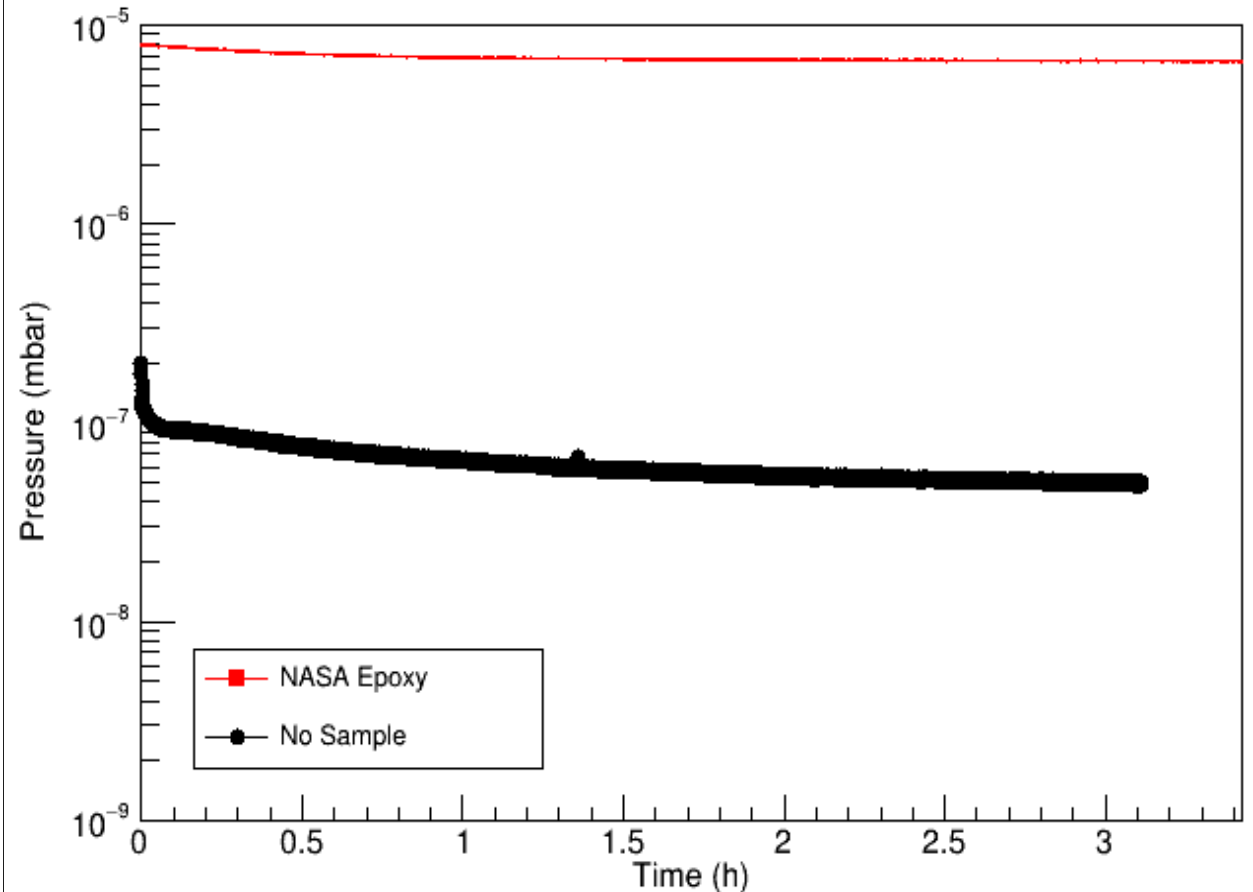
- Comparing the vacuum level with and without sample
- Comparing residual atmosphere of vacuum chamber with and without sample using RGA
- Comparing the mass of sample before and after pumping

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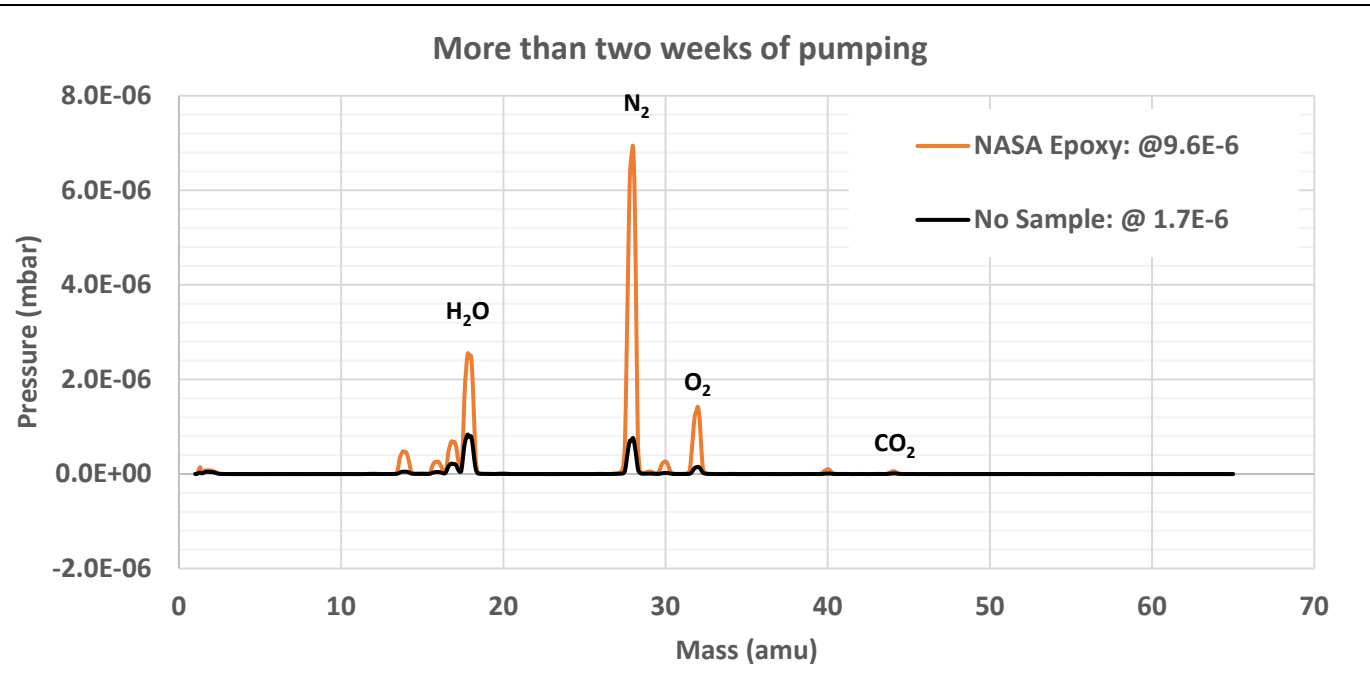
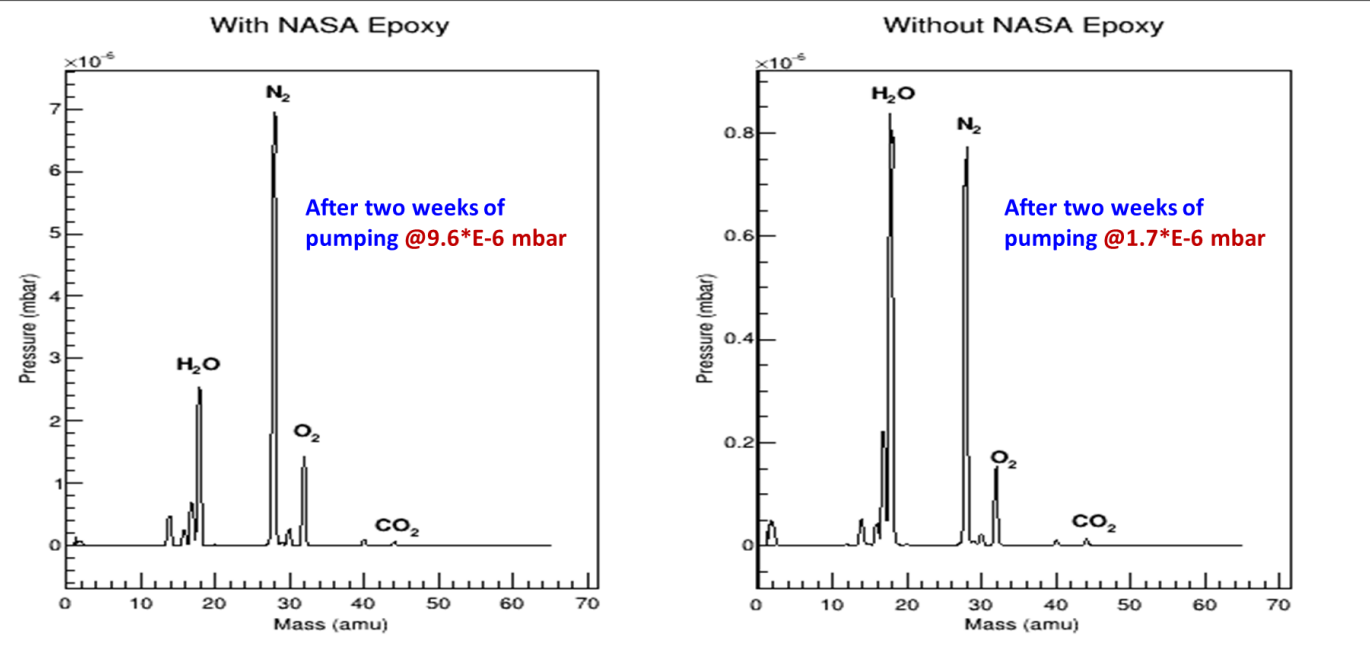
Outgassing under vacuum



How to perform outgassing measurement?

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- Comparing the vacuum level with and without sample
- Comparing residual atmosphere of vacuum chamber with and without sample using RGA
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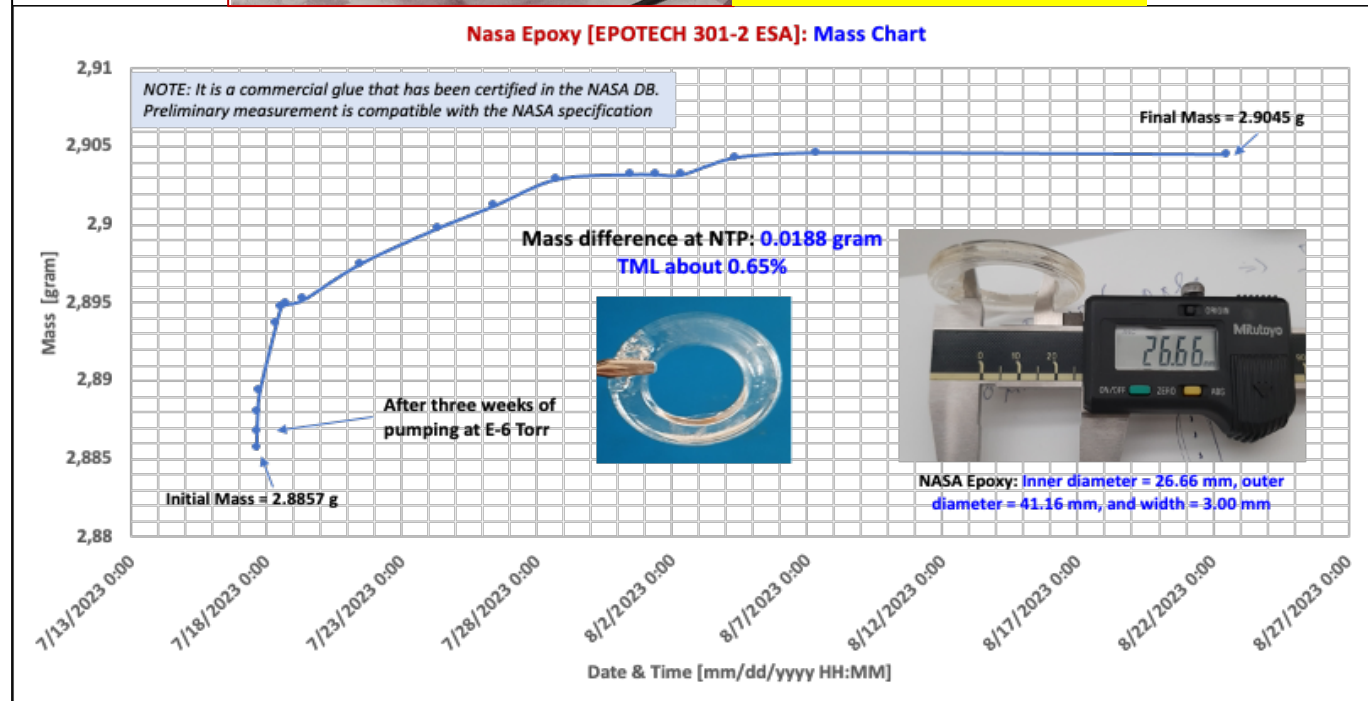
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- Comparing the vacuum level with and without sample
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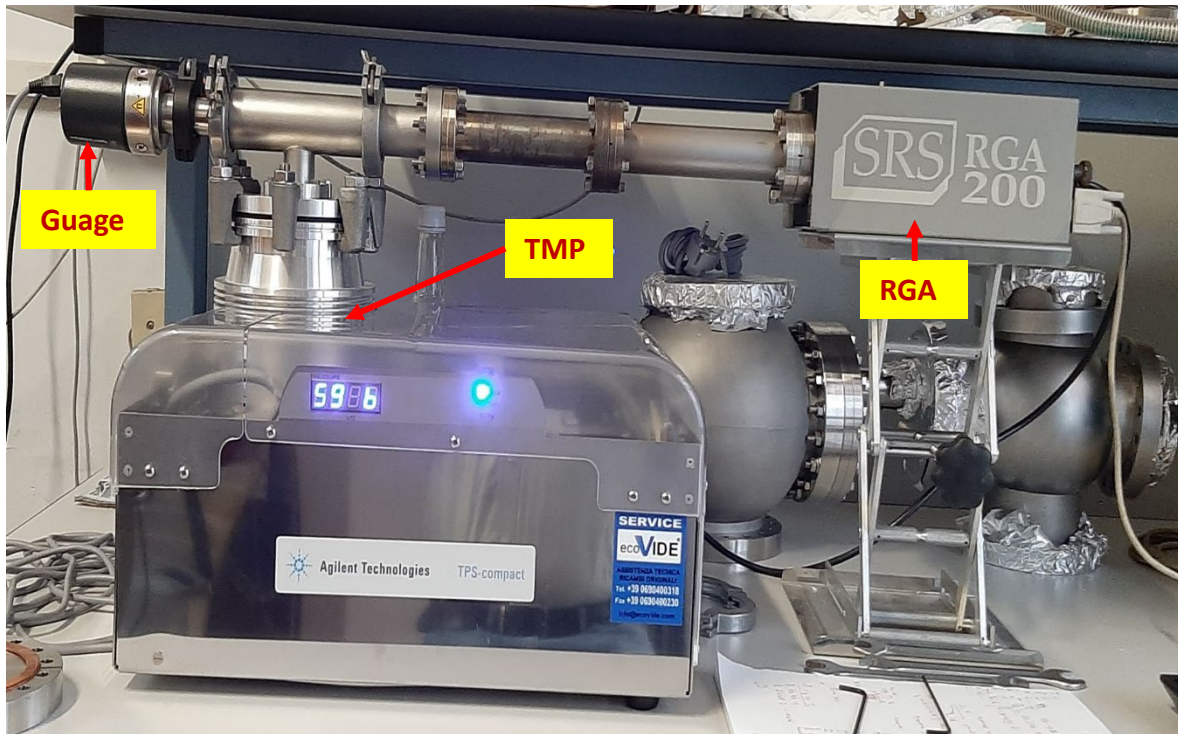


Analytical balance
(Radwag AS 110-R2):
Res 0.1 mg

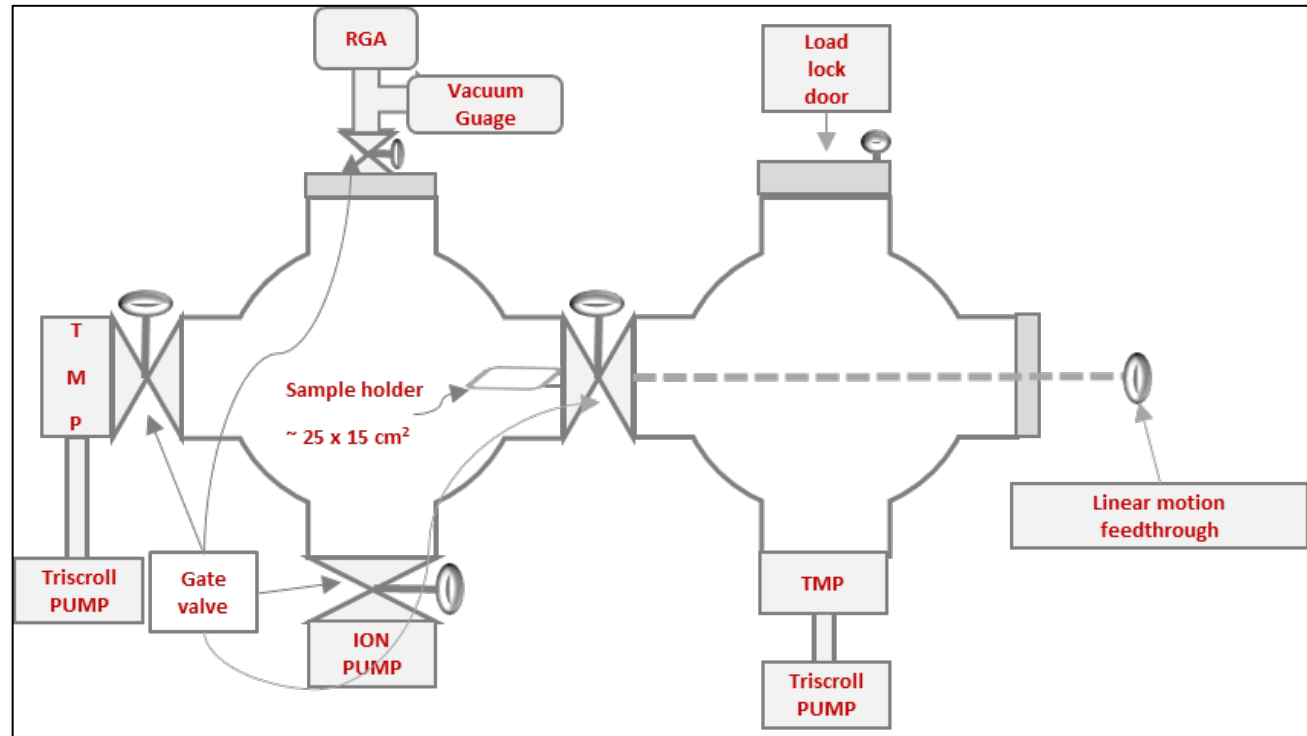


Available experimental facility and plans?

Currently running setup up to 10^{-6} mbar



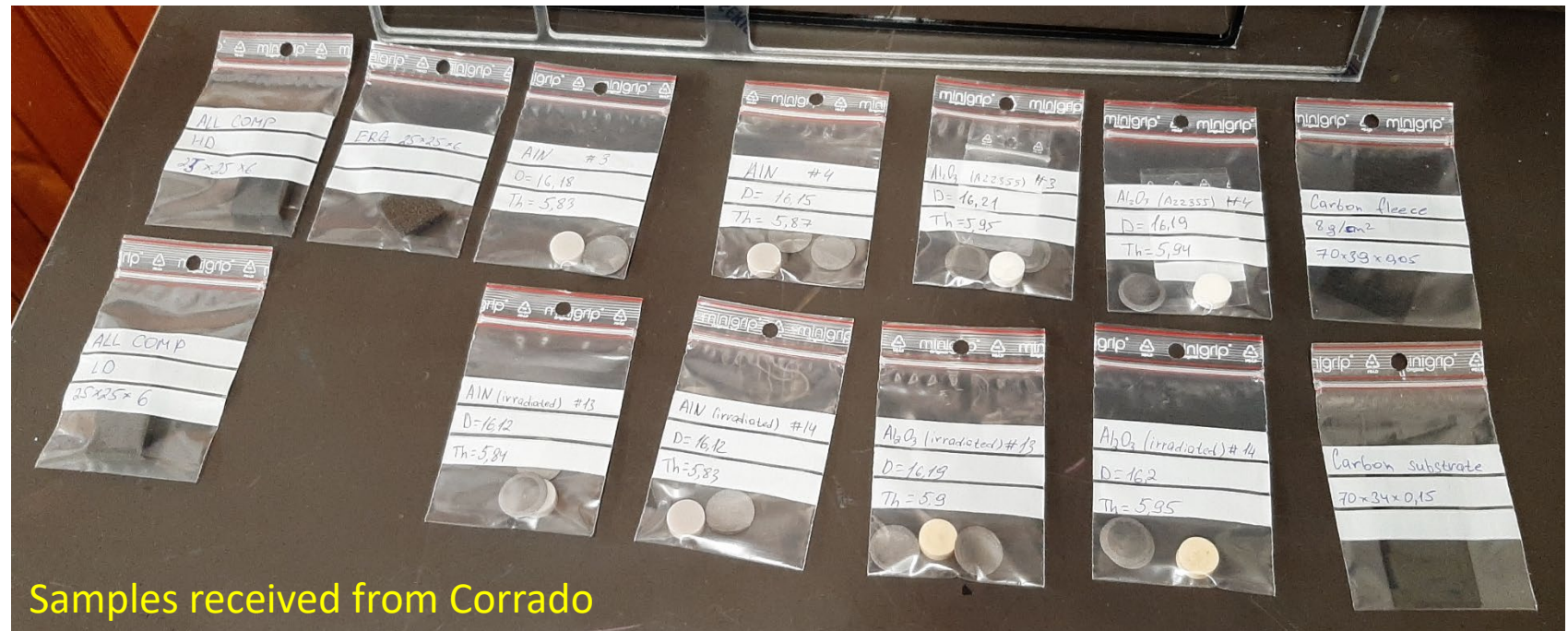
Future setup up to 10^{-10} - 10^{-11} mbar



Samples to test in vacuum environment

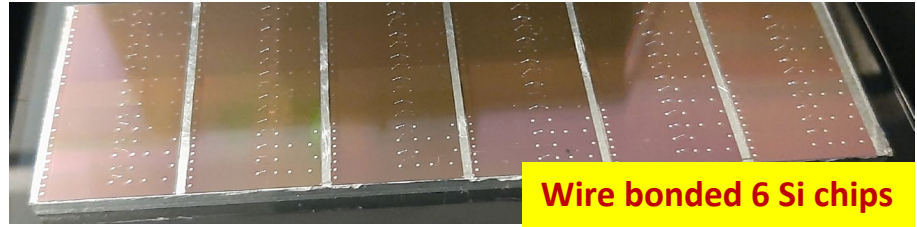
Samples:

- Carbon (LAYPUS) Substrate of the cold plate
- Carbon Fleece of the cold plate
- Carbon foam All comp high density
- Carbon foam All comp low density
- Carbon foam ERG duocel
- Optical Fiber with connector
- NASA Epoxy
- Si wafer
- Wire bonded Si wafer
- FPC
- 3D printed aluminium nitride (AlN) samples disks
- Al₂O₃ samples disk: 3D printed alumina (Al₂O₃) samples disks
- 3D printed AlSi samples disks



Preliminary Experimental Results @ 10^{-6} mbar

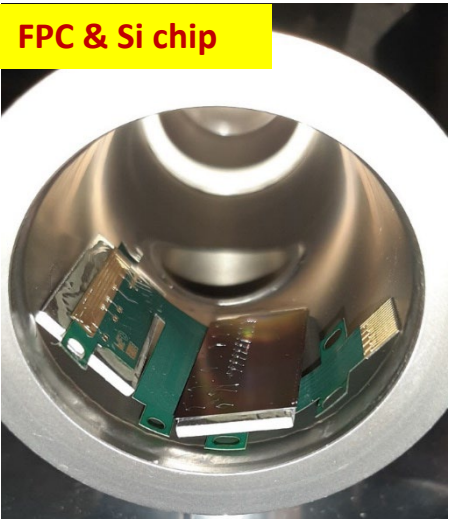
List of components : preliminary studied



Wire bonded 6 Si chips

Samples:

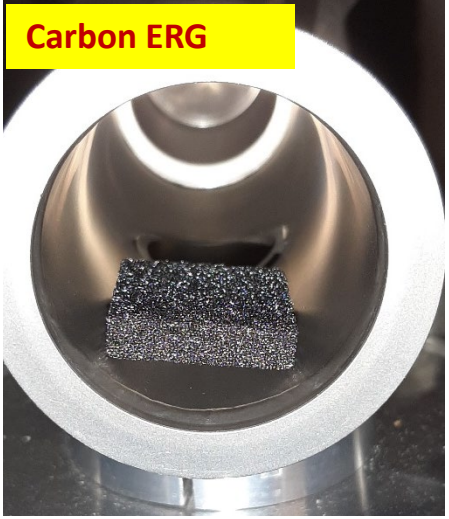
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FPC & Si chip



Carbon Fleece



Carbon ERG



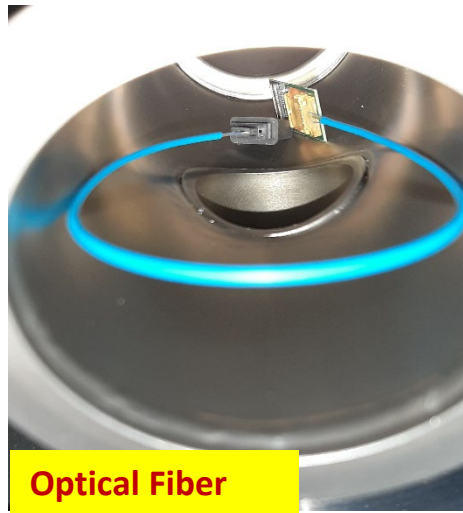
Carbon LD



Carbon Substrate



Carbon HD

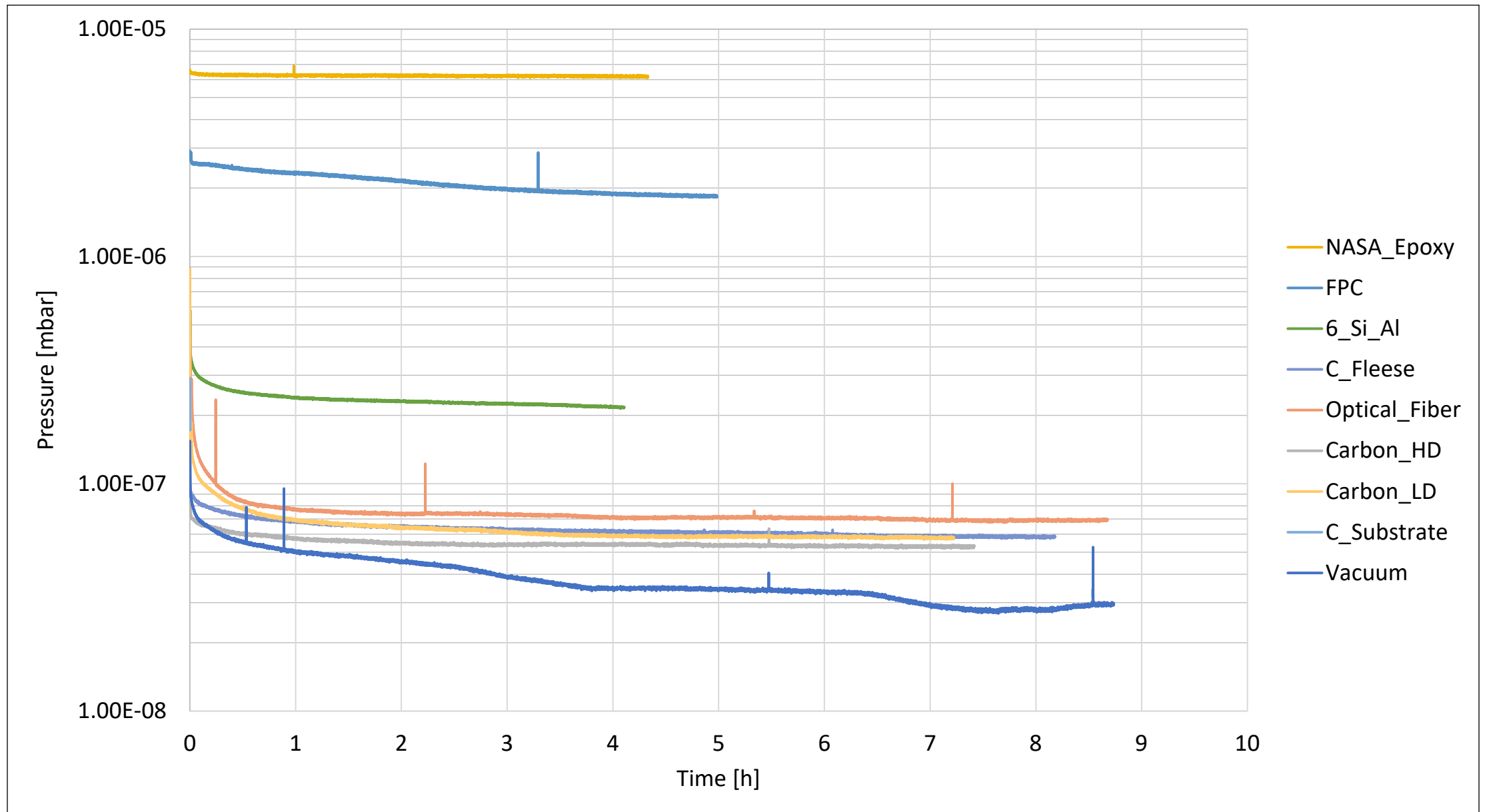


Optical Fiber

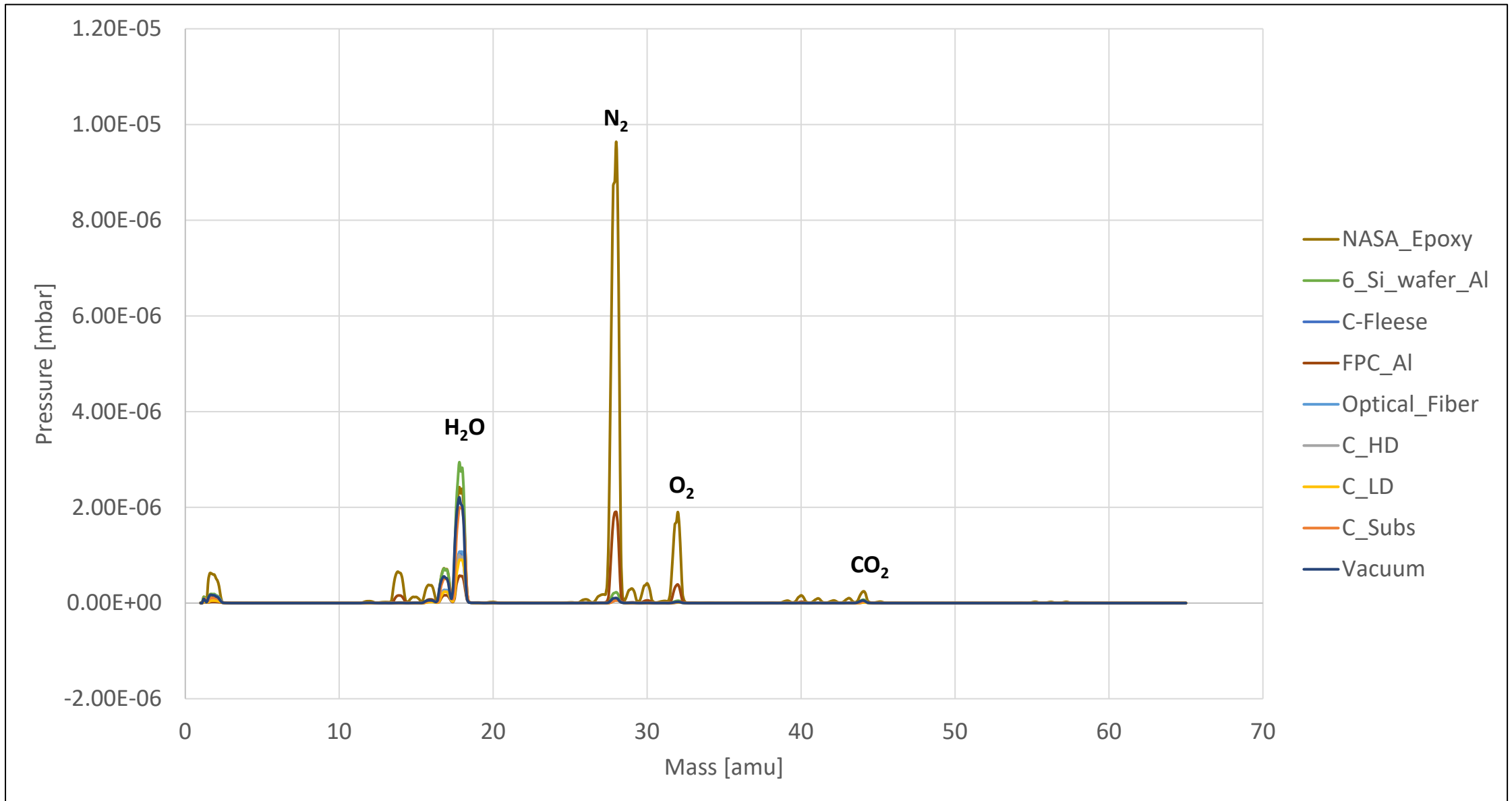


Carbon Substrate

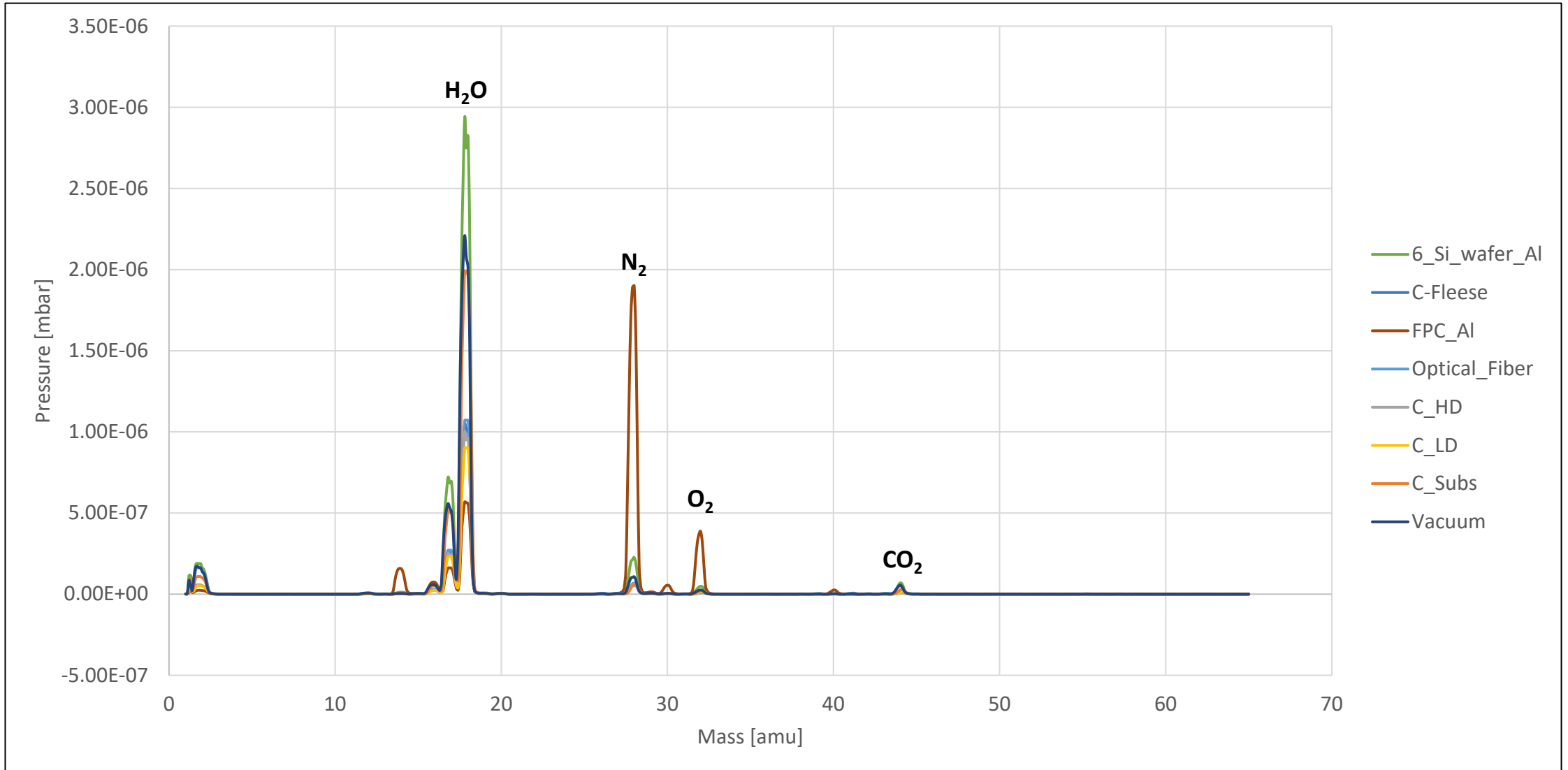
Outgassing under vacuum (1E-6 mbar)



Residual gas compassions: under vacuum (1E-6 mbar)



Residual gas compassions: under vacuum (1E-6 mbar)

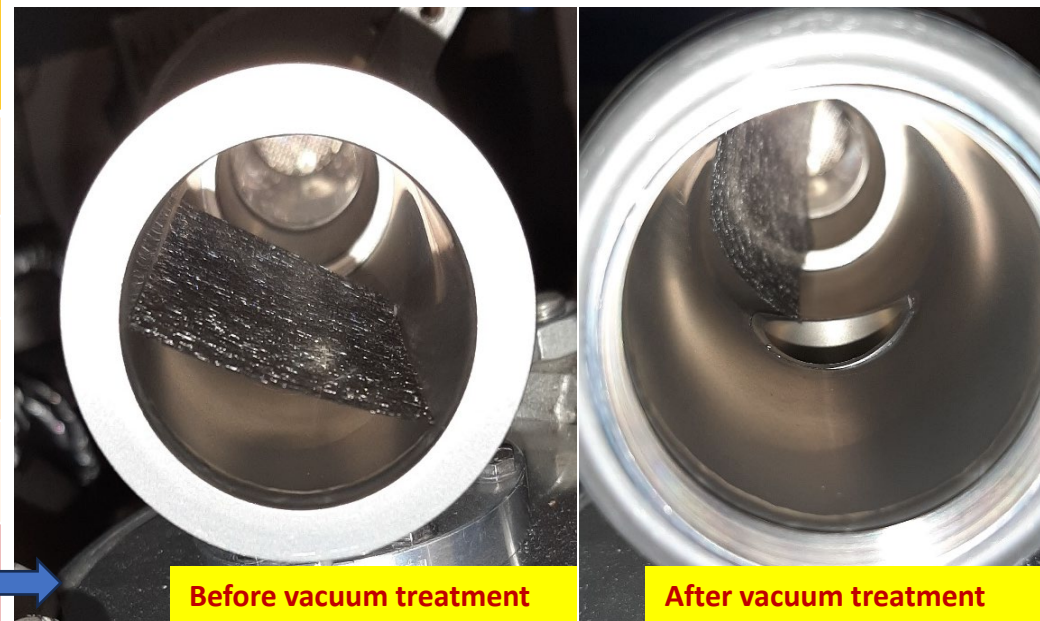


Total mass loss [TML]: under vacuum (1E-6 mbar)

Samples	TML [%] (Just after vacuum treatment)	TML [%] (Regained after vacuum treatment)
NASA_Epoxy	--	0.65
FPC_AI	--	0.05
Si_Wafer_AI	--	0.050
3_Si_Wafer_AI	0.01	0.01
C_Fleese	1.82	0.46
C_HD	0.47	-0.01
C_LD	0.73	0.01
C_Substrate	0.20	0.14
Optical_Fiber	0.32	0.14
C_ERG	11.85	12.23

Total mass loss [TML]: under vacuum (1E-6 mbar)

Samples	TML [%] (Just after vacuum treatment)	TML [%] (Regained after vacuum treatment)
NASA_Epoxy	--	0.65
FPC_Al	--	0.05
Si_Wafer_Al	--	0.050
3_Si_Wafer_Al	0.01	0.01
C_Fleese	1.82	0.46
C_HD	0.47	-0.01
C_LD	0.73	0.01
C_Substrate	0.20	0.14
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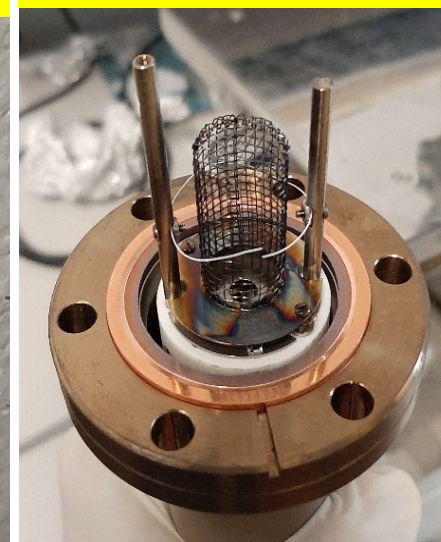
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Carbon ERG fibers: after vacuum treatment



Broken filament : after Carbon ERG vacuum treatment

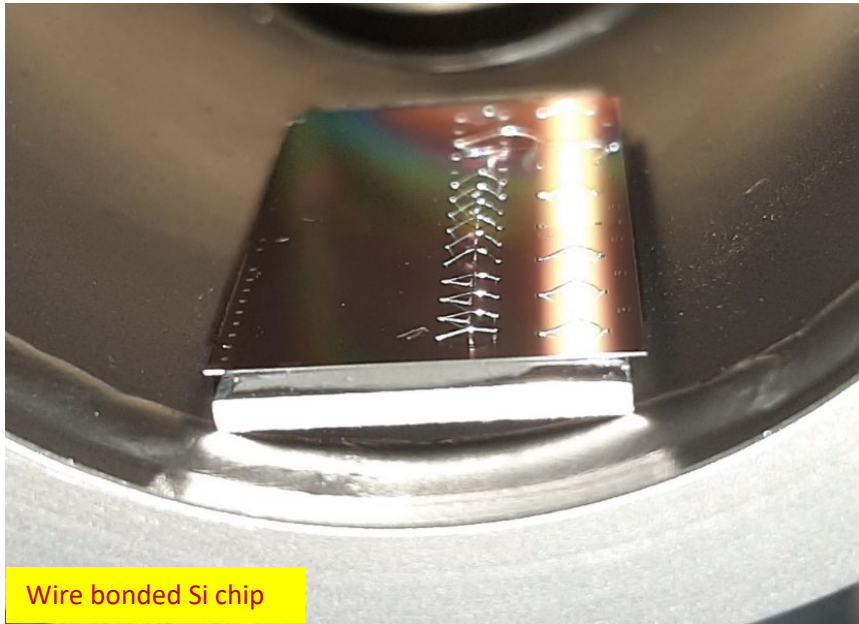


WIRE-BONDING STUDY UNDER VACUUM

wire bonded Si wafers and required setups: Pulling force test

Setup description:

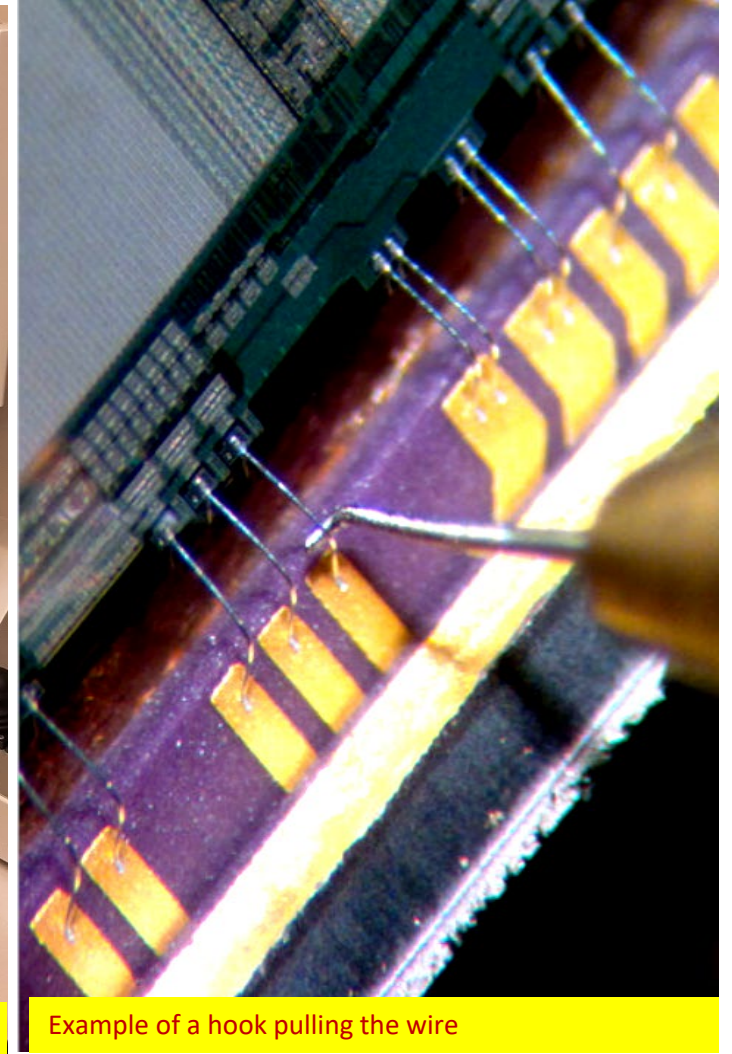
- ❑ 6 ALPIDE chips glued on metallic support and wire bonded
- ❑ Each chip having 14/15 wires bonded
- ❑ To disentangle eventual chip-to-chip variation
 - ❑ 44 pull test without vacuum treatment
 - ❑ 44 pull test after vacuum treatment



Wire bonded Si chip



wire bonded pulling force test measurement setup

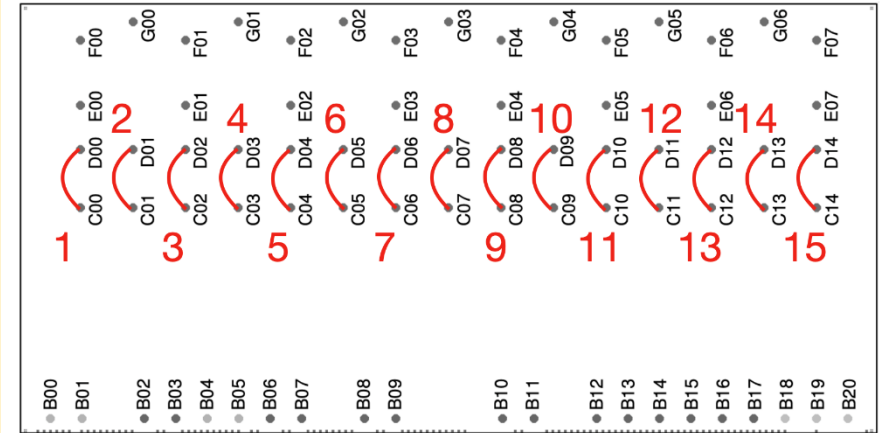


Example of a hook pulling the wire

Experiment execution dates:

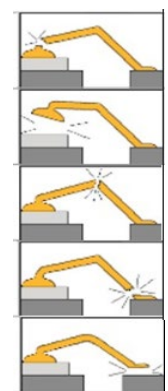
- Chips mounted and pull-force tested on **6/20/2023**
- Samples kept under vacuum (10^{-6} bar) for **~10 days**
- Pull-force measurement after vacuum treatment on **19/20/2023**

wires distribution between the ALPIDE's pads''



CHIP	Without VACUUM Pull-force average \pm sigma (min - max) g [# of wires]	After VACUUM Pull-force average \pm sigma (min - max) g [# of wires]
#1	8.37 \pm 1,50 (6,5 - 11.1) [8]	8.23 \pm 0.95 (6.80 – 9.45) [6]
#2	8.00 \pm 1.90 (7.08 - 10.67) [6]	7.28 \pm 2.62 (4.58 - 12.54) [8]
#3	8.92 \pm 2.11 (6,04 – 12.30) [8]	8.90 \pm 1.68 (7.14 – 11.39) [7]
#4	8.56 \pm 2,42 (4.50 - 12,.9) [7]	9,04 \pm 1.53 (7.02 - 11.06) [8]
#5	9.72 \pm 0.66 (8.88-10.57) [8]	9.20 \pm 0.83 (8.12 – 10.88) [7]
#6	7.09 \pm 1.73 (4,42 – 9.55) [7]	8.32 \pm 1.12 (6.35 - 9.57) [8]
TOT	8.49 \pm1.87 (4.42 - 12.59) [44]	8.50 \pm1.66 (4,59 - 12,54) [44]

CHIP	Without VACUUM (44 wires)					After VACUUM (44 wires)				
	1	2	3	4	5	1	2	3	4	5
#1	6	1	0	0	1	2	2	0	1	1
#2	2	1	0	0	3	0	1	0	5	2
#3	4	2	0	0	2	1	2	0	4	0
#4	4	0	0	1	2	0	5	0	2	1
#5	7	0	0	0	1	1	3	0	2	1
#6	3	3	0	0	1	0	5	0	2	1
TOT	26	7	0	1	10	4	18	0	16	6



- 1 – Breakage at the 1st foot
- 2 – Lift-off at the 1st foot
- 3 – Breakage at the apex of the loop
- 4 – Breakage at the 2nd foot
- 5 – Lift-off at the 2nd foot

- Strong reduction of breakage at the 1st foot
- Clear increase of lift-off at the 1st foot
- Strong increase of breakage at the 2nd foot
- Moderate reduction of lift-off at the 2nd foot

Breakage/Lift-off
BEFORE vacuum: 27/17
AFTER vacuum: 20/24

Experimental Facilities @ INFN Bari

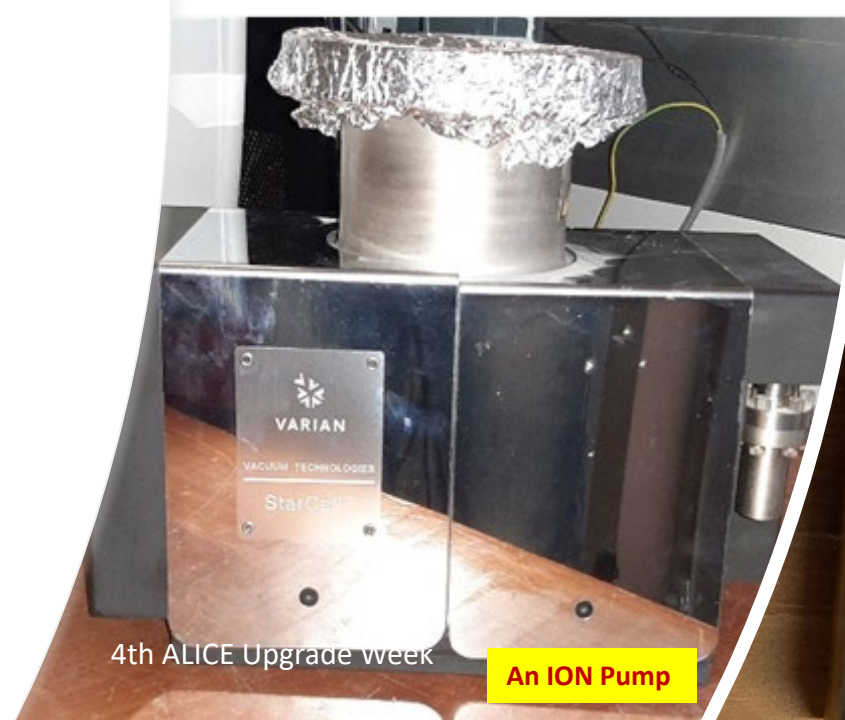
- Two SS 4-way cross spherical vacuum chambers
- All kind vacuum pumps (Primary + TMP +ION)
- Gate valves (Cf-150, cf-100, kf-40)
- Display and control units for all types of pumps
- All types of vacuum gauges and display unit



A 4 way-cross SS spherical chambers



HOT Cathode guages



An ION Pump



A CU gasket-based GATE VALVE

Future experimental facilities to be assembled @ INFN Bari

Experimental setup: *vacuum SS chambers with associated equipment to reach 10^{-10} mbar pressure*

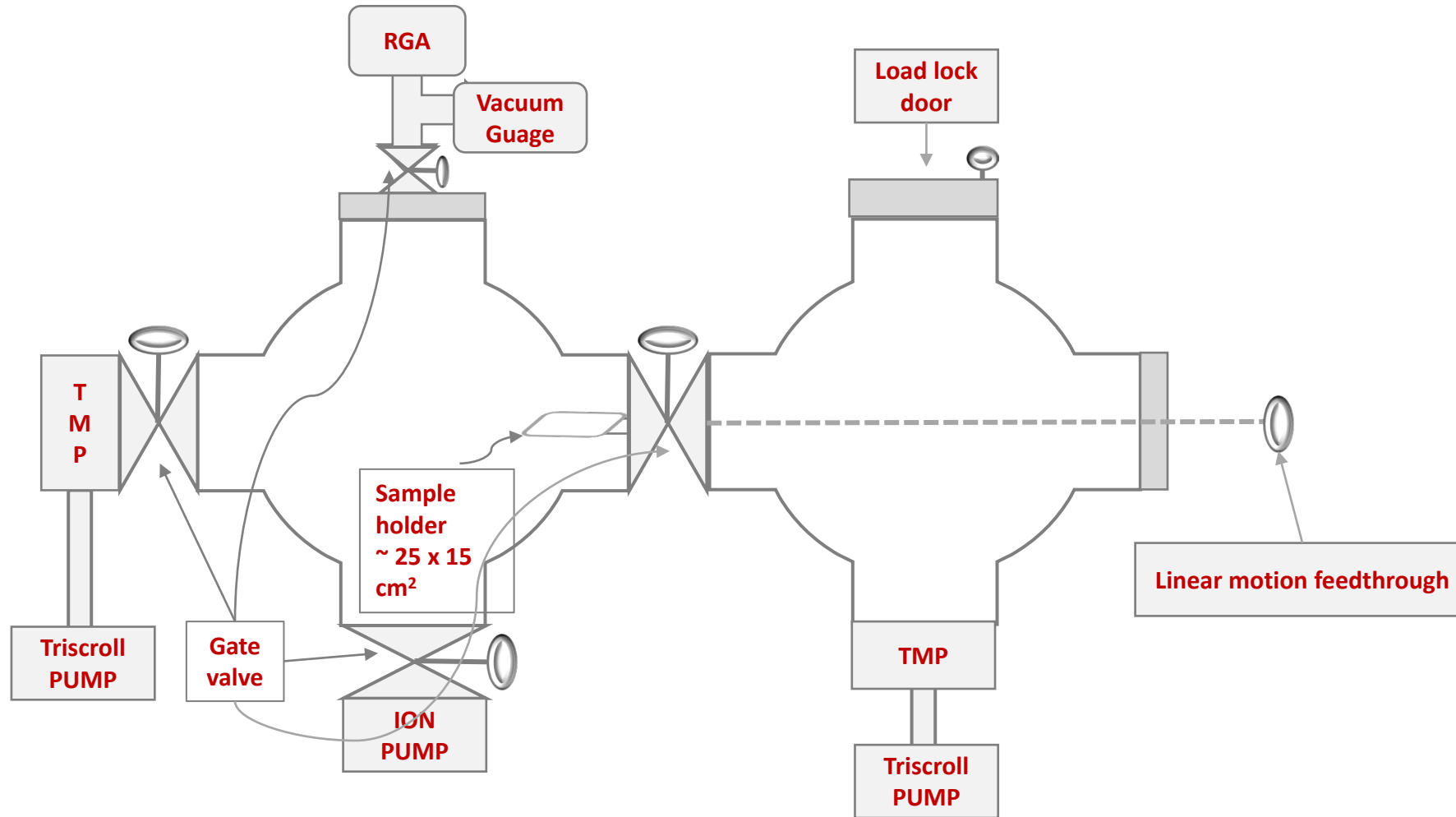


Fig: Schematic diagram of a four-way cross ~ 20 cm diameter SS spherical chamber are available with all type of pump and RGA

Experimental setup: *vacuum SS chambers with associated equipment to reach 10^{-10} Torr pressure*

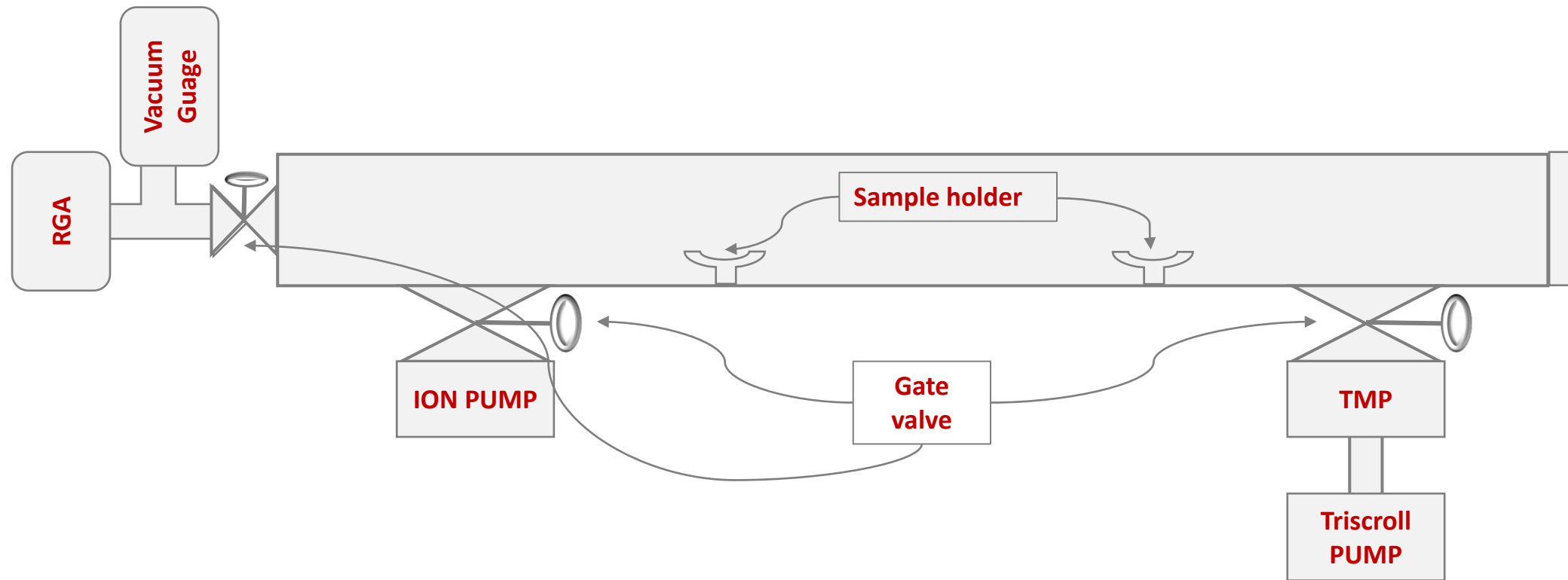


Fig: Schematic diagram of a future SS cylindrical chamber need to build a/c to detector dimension together with required vacuum pumps and RGA

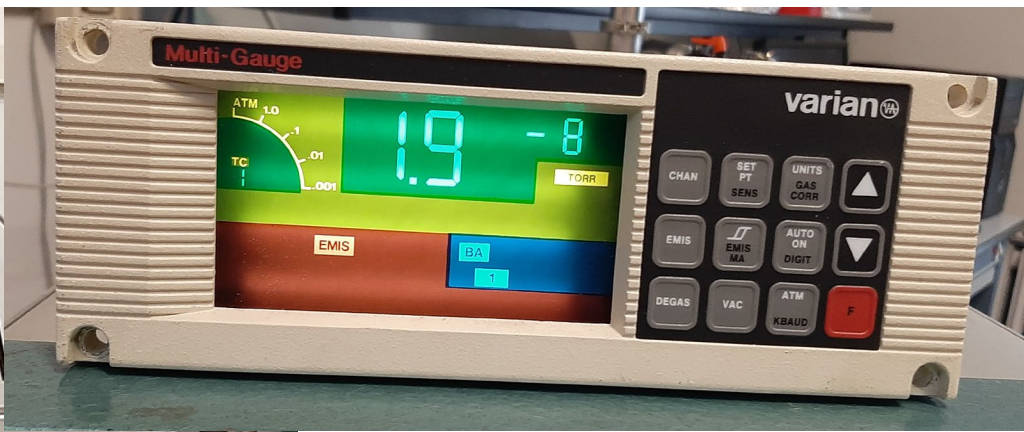
Future plans

- Need to build a vacuum chamber with a vacuum of the order of $\sim 10^{-10}$ Torr
 - All gaskets and gate valve must be metallic
 - Heating tape and heating lamp are essential
 - Proper cleaning with ultrasonic bath in distilled water followed by alcohol
 - All types of vacuum pumps (primary, TMP & ION) are available
- Measurements to perform
 - Outgassing study
 - Residual gas atmosphere study
 - Total mass loss (TML) study
 - Wire bonding strength study
 - Gluing strength
- Samples to be test
 - All IRIS detector components
 - Glue for IRIS detector
 - Wire bonded Si chips
 - FPC
 - Optical fiber cable

HOT cathode gauge

TMP controller

DCU



Reached **1.9E-8** Torr pressure in 24 hours of pumping : Without any ION pump and heating tape running

Thank you

Metallic gate valve

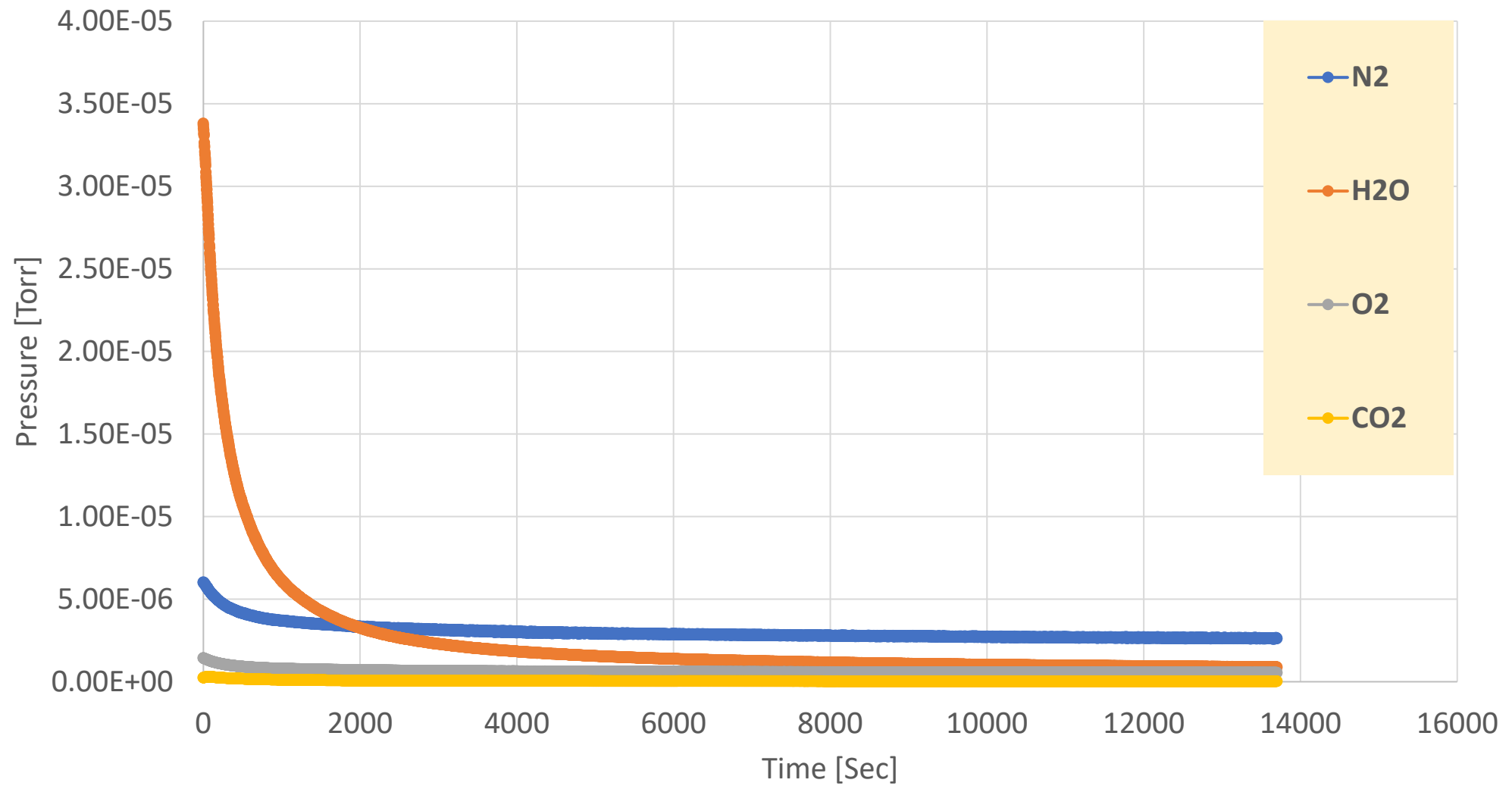
ION pump

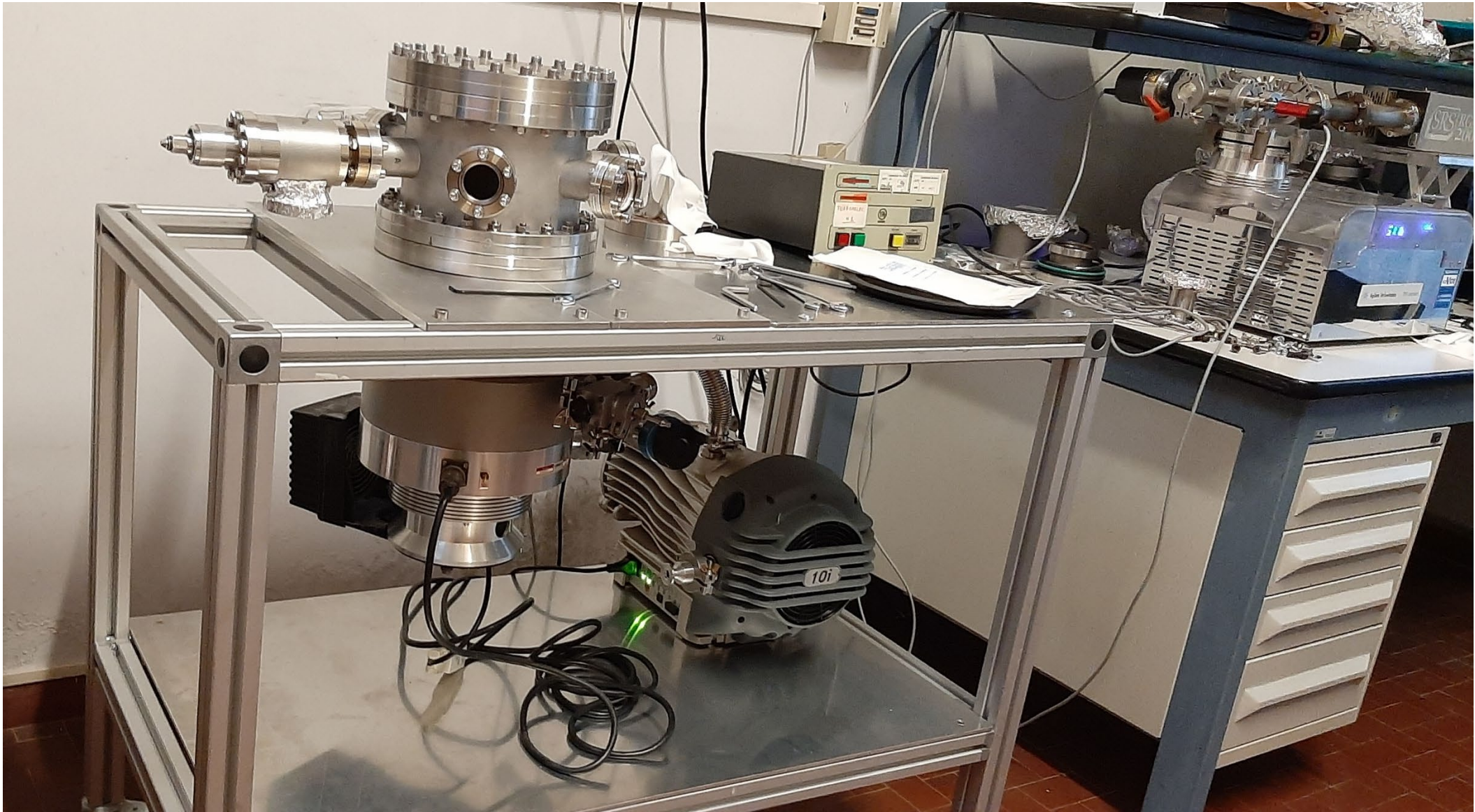
TMP pump

Triscroll vacuum pump

Thank you

Si_FPC_Al: immediately after pumping started

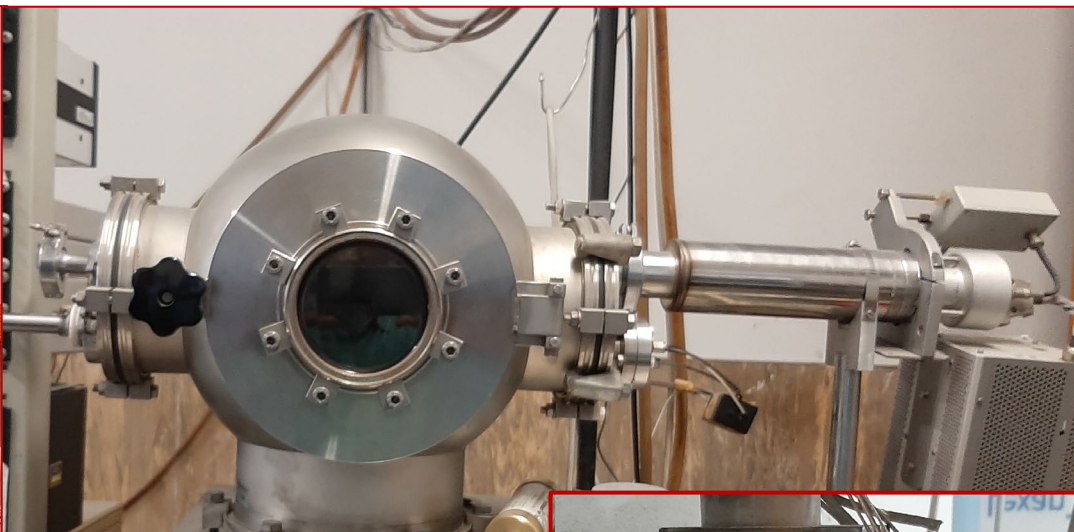




Instruments @INFN Bari – Italy:



Pictorial view of a 5-way cross vacuum chamber @ INFN Bari - Italy



Front view of the vacuum chamber @ INFN Bari - Italy



A Dual Gauge for monitoring the order of vacuum @INFN Bari - Italy



An Agilent turbo molecular pump, with pumping speeds of 300 L/s



A RADWAG (AS 110.R2) Analytical Balances machine @INFN Bari -Italy

CsI coating for ALICE HMPID have been performed with above setup

Available vacuum pumps



Fig: Primary vacuum pumps

12/1/2023



Fig: Turbo molecular pump

4th ALICE Upgrade Week

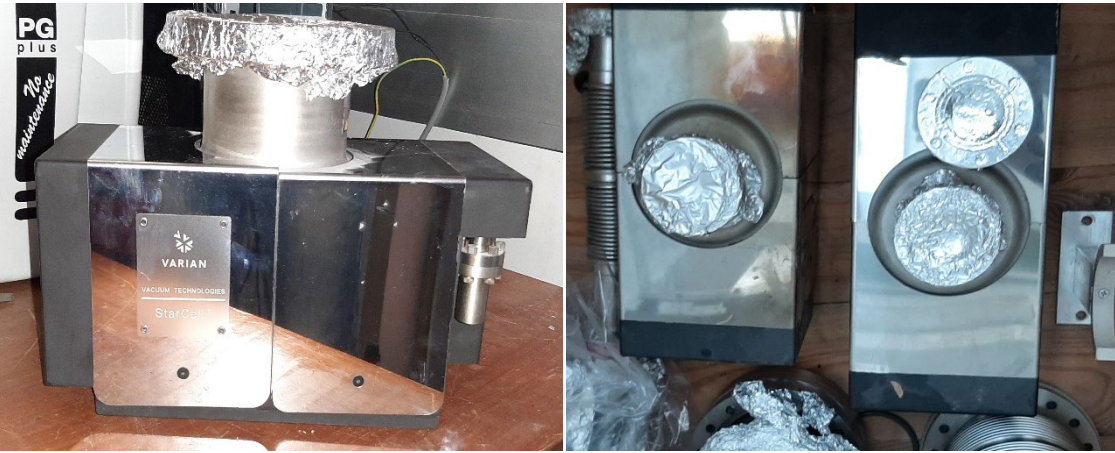
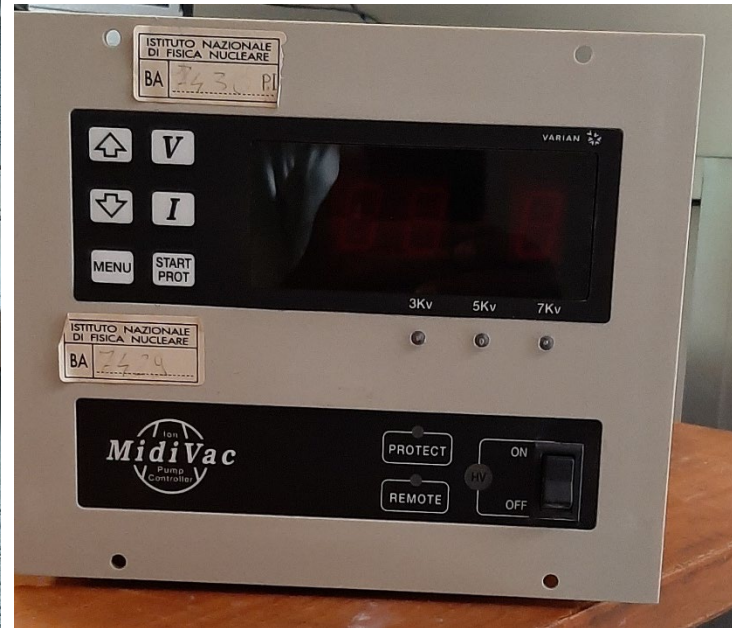


Fig: ION pumps

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Display and control units

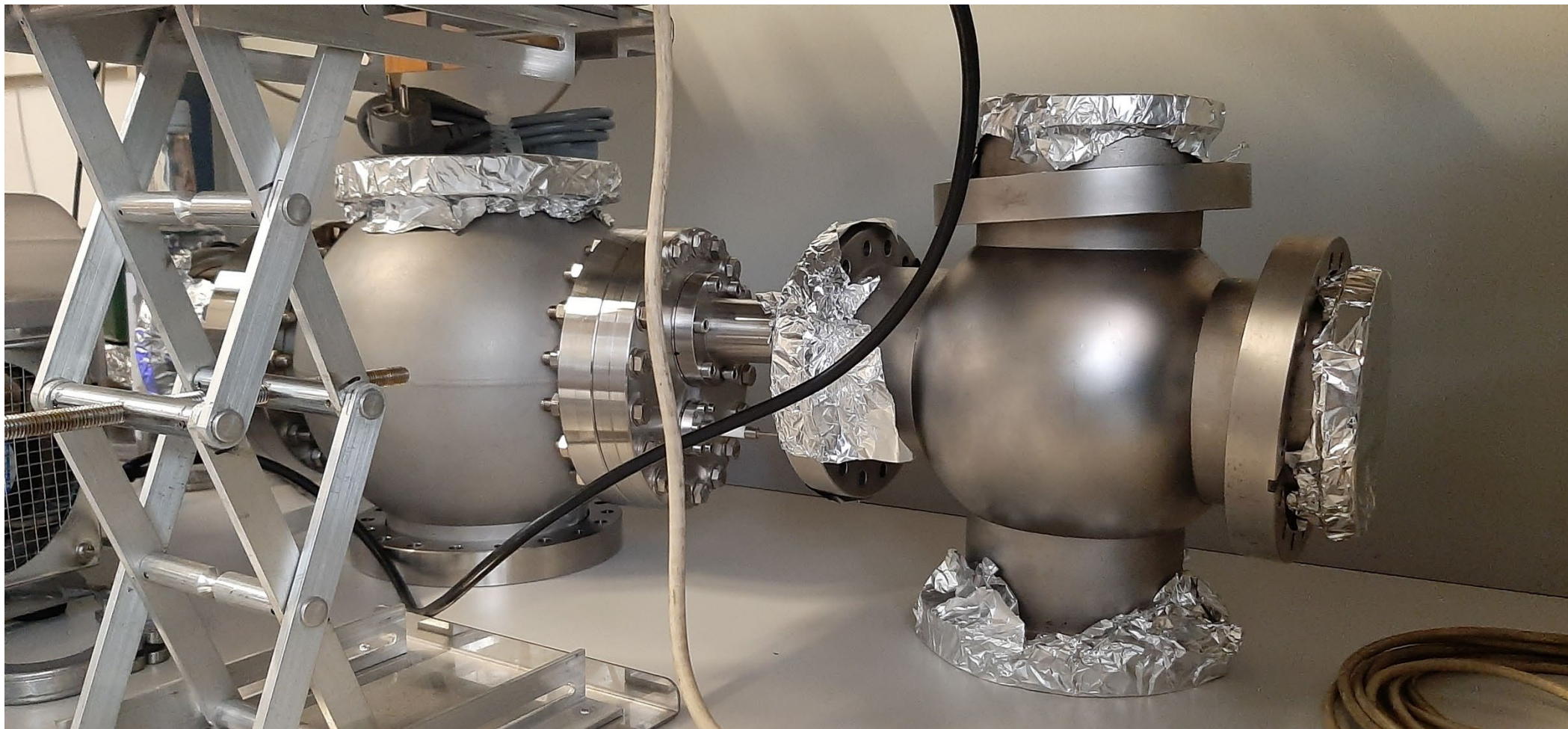


Available vacuum gauges and display unit



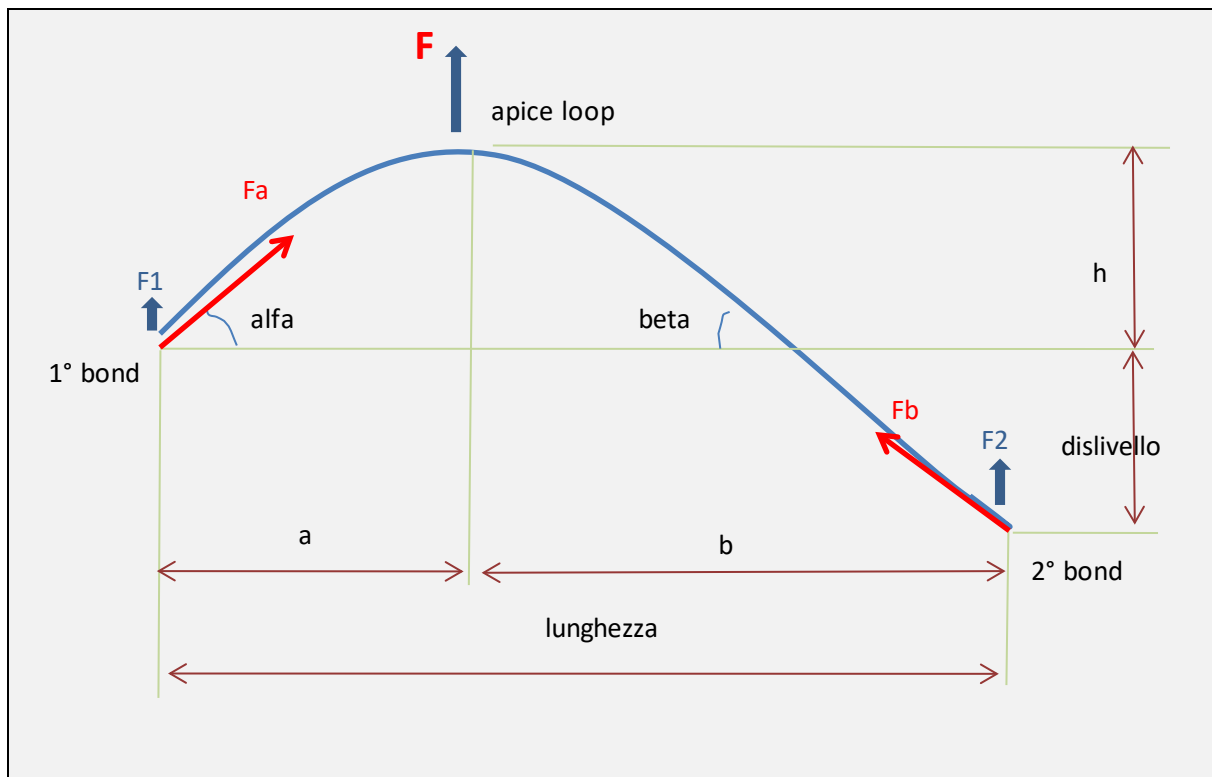
Fig: Vacuum gauges and display unit

Available vacuum chambers



Available gate valves

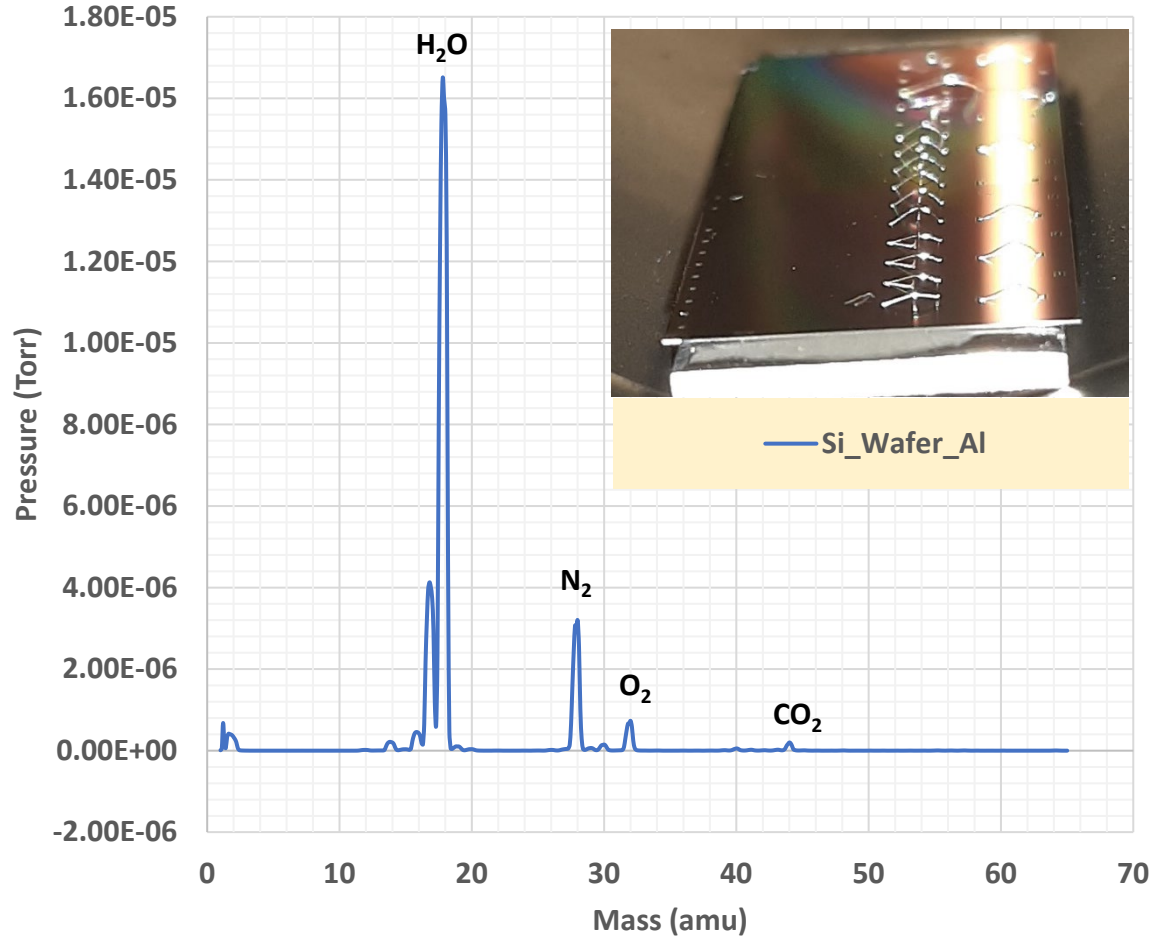




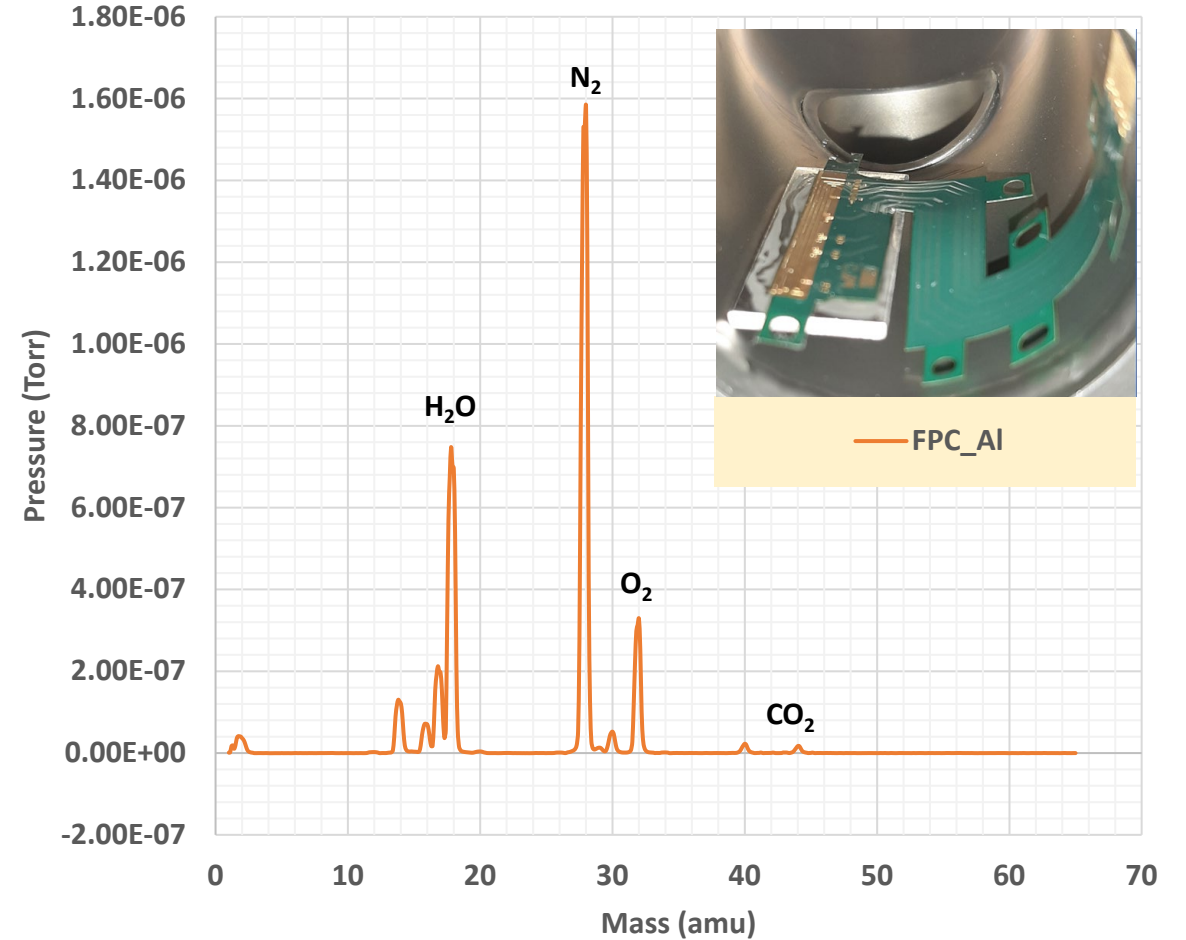
	1° bond	2° bond	apice loop	
X	21140	21126	21140	
Y	85014	82988	84001	
bond height e/o focus	11795	11795	11225	
Length	2026		forza	9.46
height difference	0			
h	570		Fa	9.8
a	1013		Fb	9.8
b	1013			
angolo alfa	29		F1	4.8
angolo beta	29		F2	4.8
angolo strappo dinamometro	0			

Si wafer and FPC: Residual gas atmosphere study

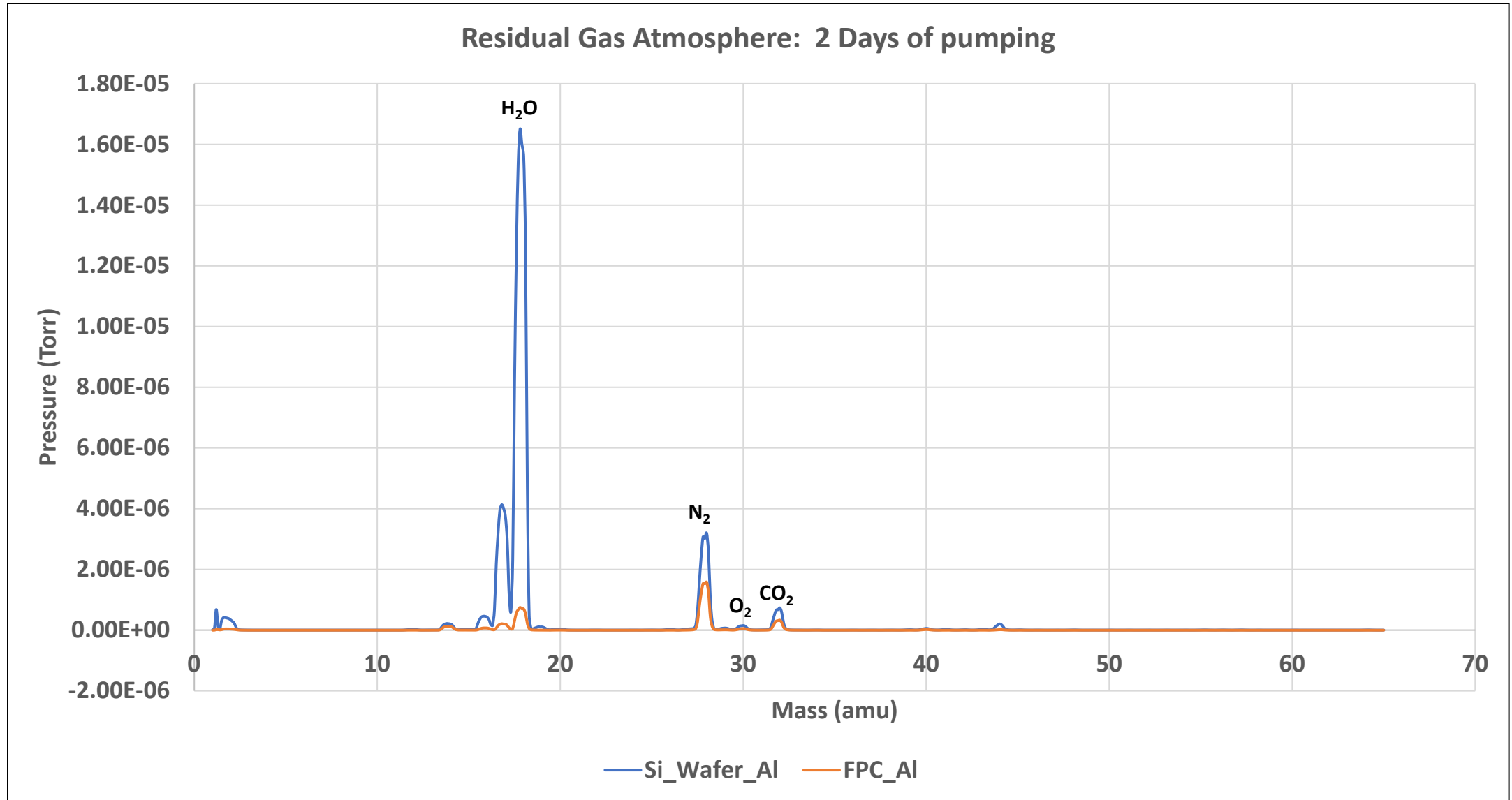
Residual Gas Atmosphere: 2 Days of pumping



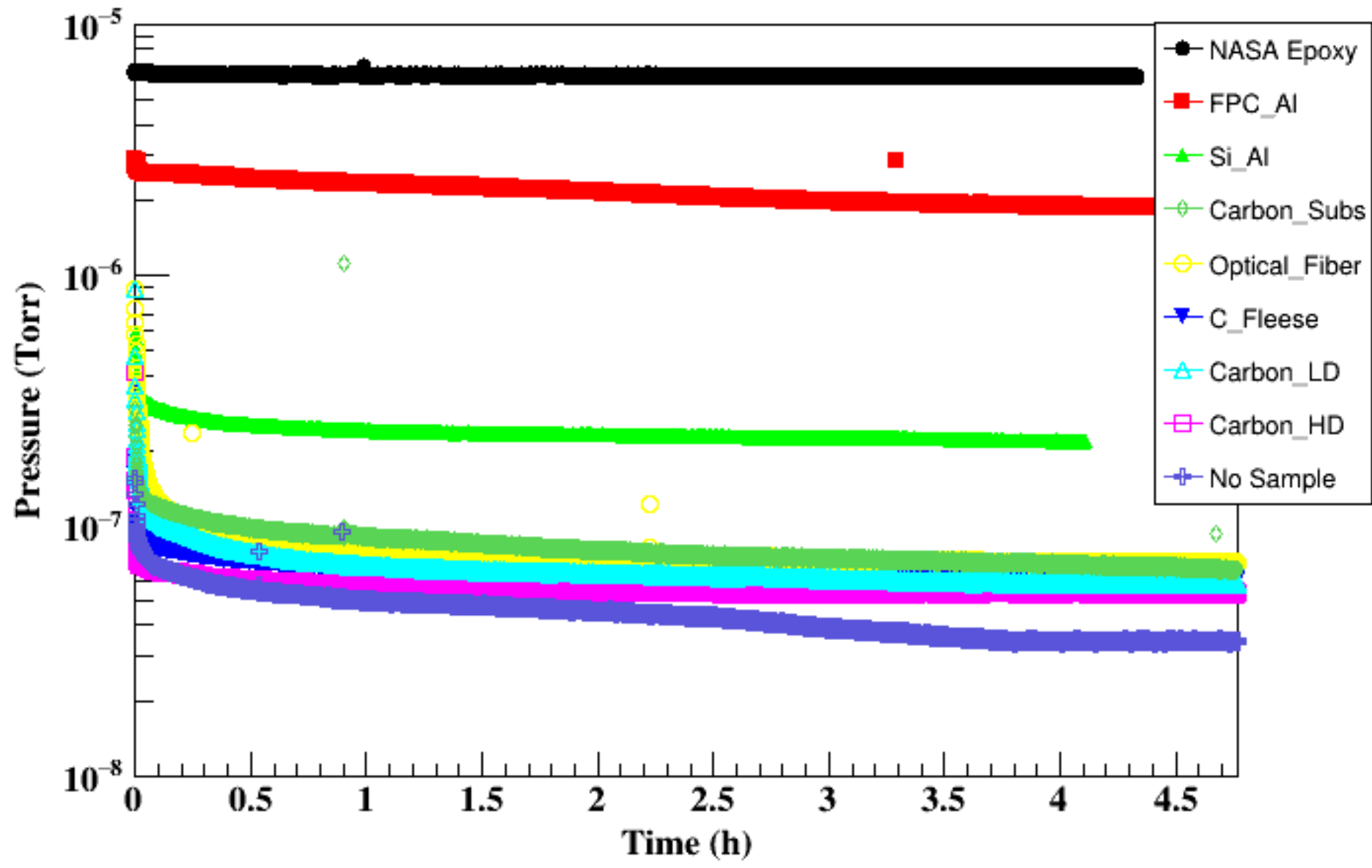
Residual Gas Atmosphere: 2 Days of pumping



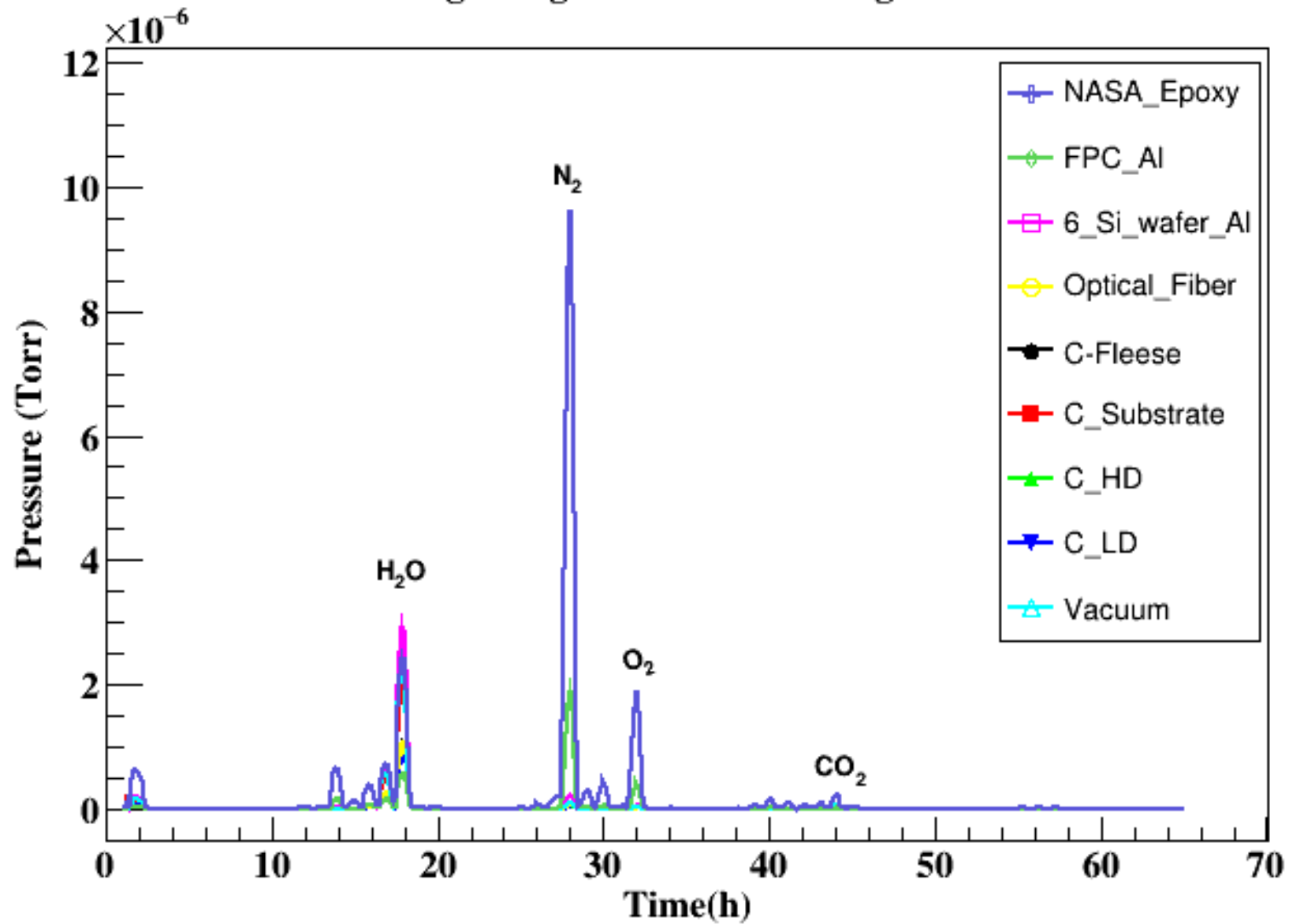
Si wafer and FPC: Residual gas atmosphere study



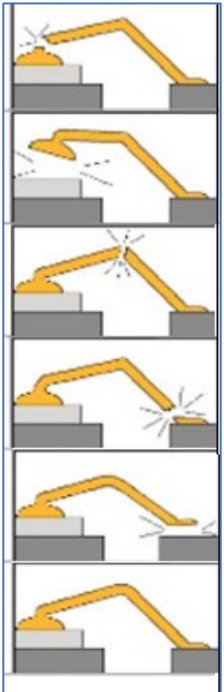
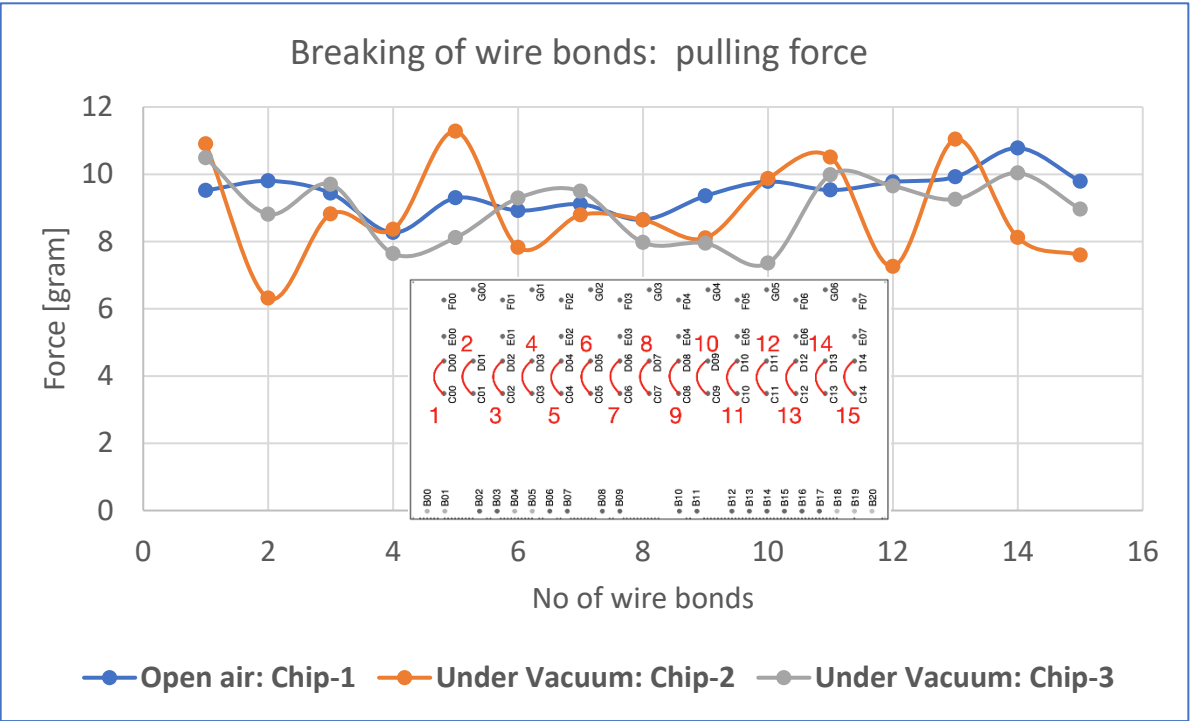
Outgassing under vacuum



Outgassing in vacuum: Analog scans



Pulling force test: preliminary results



Failure modes	Chip 1	Chip 2	Chip 3
Breakage at the first foot	12	7	9
Lift off at the first foot	0	5	5
Breakage at the apex of the loop	0	0	0
Breakage at the second foot	0	1	0
Lift off at the second foot	3	2	1
Ddouble loop hooked	0	0	0

Pulling force	chip 1: As received	chip 2: 11 days in vacuum @ E-6	chip 3: 11 days in vacuum @ E-6
Minimum	8.27	6.32	7.36
Maximum	10.78	11.28	10.49
Medium	9.46	8.90	8.98
Sigma	0.59	1.50	0.97

- ❑ Pull force before and after vacuum treatment: compatible within statistical error
- ❑ Lift off failure increased after vacuum treatment
- ❑ More statistics will be added for clear understanding

Samples to test in vacuum environment

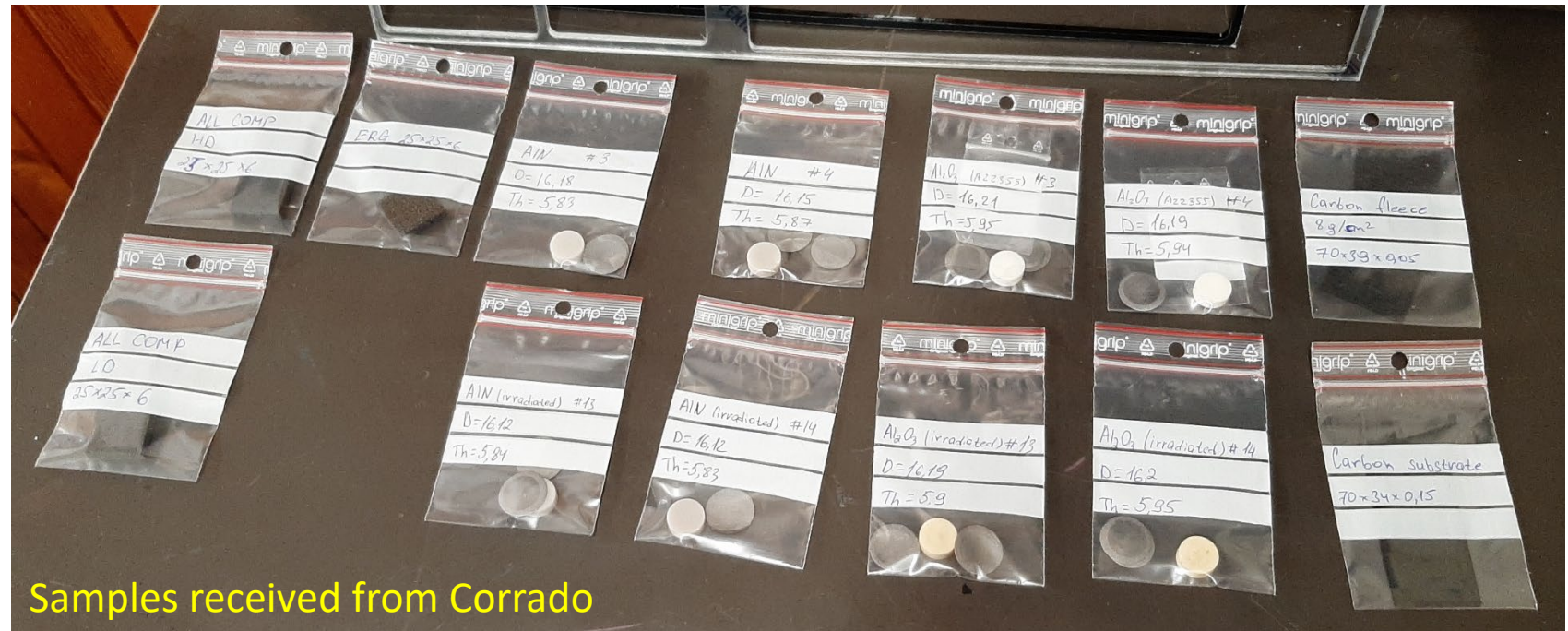
- Sample received from Corrado Gargiulo
 - 3D printed aluminium nitride (AlN) samples disks
 - Al₂O₃ samples disk: 3D printed alumina (Al₂O₃) samples disks
 - 3D printed AlSi samples disks
 - Carbon (LAYPUS) Substrate of the cold plate
 - Carbon Fleece of the cold plate
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 - Carbon foam All comp low density
 - Carbon foam ERG duocel



Sample received from Felix

- Sample received from Felix Reidt
 - Optical Fiber with connector

- Samples tested in Bari
 - NASA Epoxy
 - Si wafer
 - Wire bonded Si wafer
 - FPC



Samples received from Corrado